



Exceptional service in the national interest

Nanostructured Materials to Negate Nanosecond Voltage Spikes

Simeon Gilbert

April 24th, 2024

Emergent Quantum Materials and Technologies
(EQUATE) Seminar

University of Nebraska – Lincoln



Focus Areas at Sandia National Laboratories



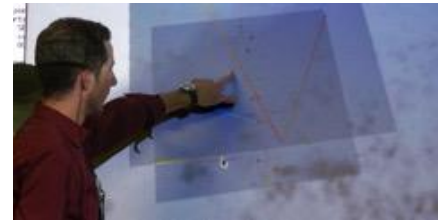
Global Security



Nuclear Deterrence



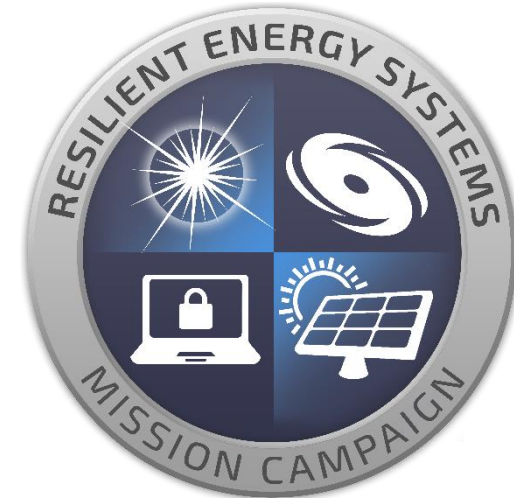
National Security Programs



Advanced Science & Technology



Energy & Homeland Security





Granular Metal Team

PI: Laura Biedermann

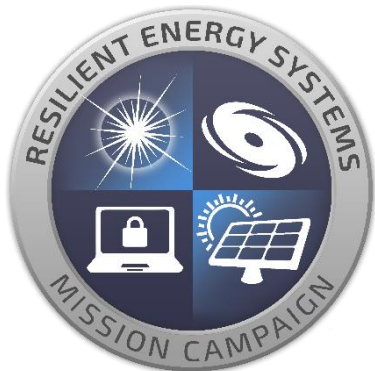
Granular metal growth: Simeon Gilbert, Michael Siegal, Doug Vodnik, Lyle Brunke

Granular metal electrical characterization: Michael McGarry, Will Bachman, Peter Sharma, Tyler Bowman, Luke Yates

Microscopy and spectroscopy: Simeon Gilbert, Melissa Meyerson, Paul Kotula, Samantha Rosenberg, Tommy Kmiecik

Device and PCB design: Jack Flicker, Rachid Darbali-Zamora, Will Bachman

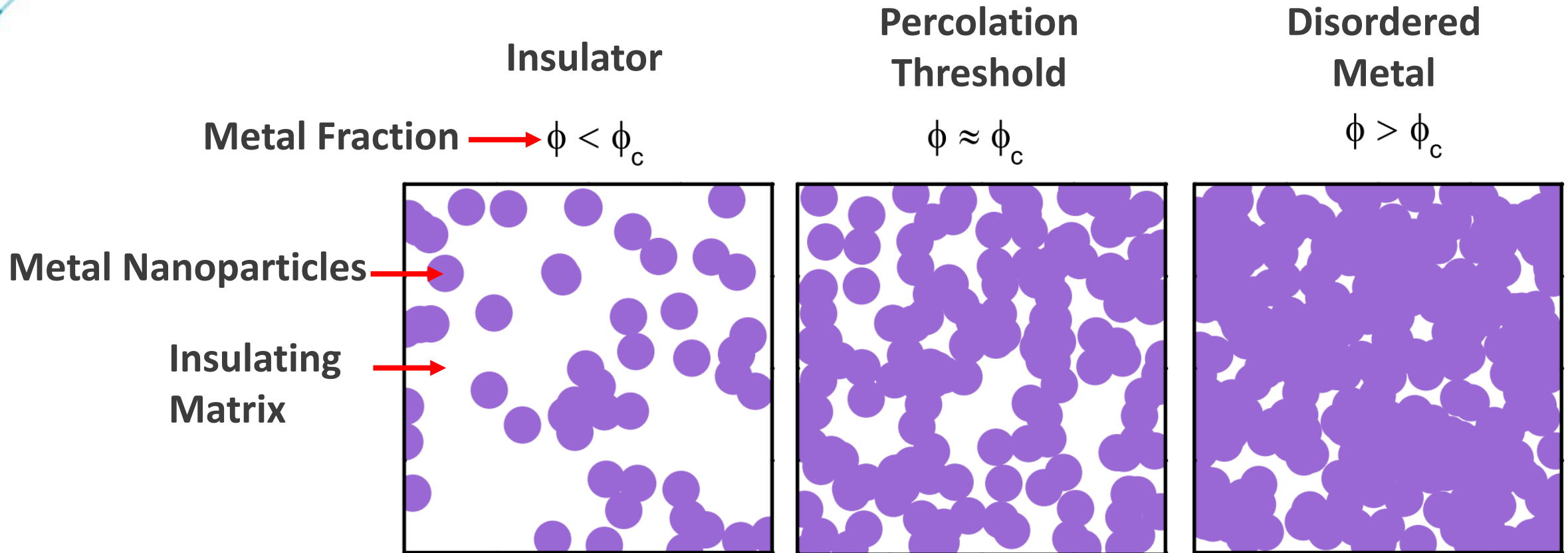
Lithography and packaging: Patrick Finnegan, Scott Weathered, Adrian Cassias, Connor Healey, Alvin Ha



This work was supported by the Laboratory Directed Research and Development program at Sandia National Laboratories. Sandia National Laboratories is a multimission laboratory managed and operated by National Technology and Engineering Solutions of Sandia, LLC, a wholly owned subsidiary of Honeywell International Inc., for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-NA0003525.



What are granular metals (GMs)?

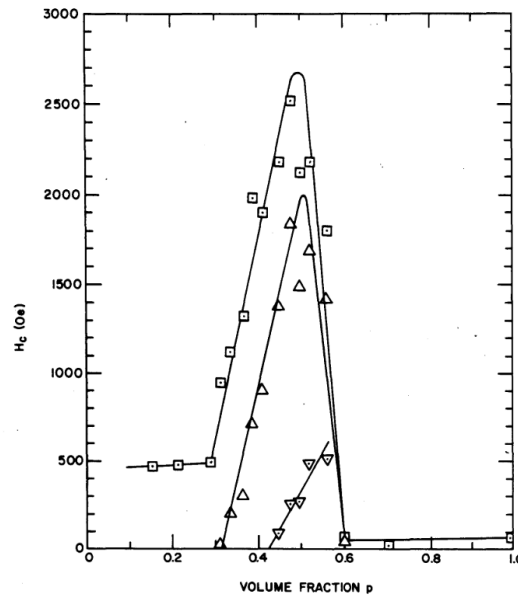


Grimaldi, Phys. Rev. B **89**, 214201 (2014)

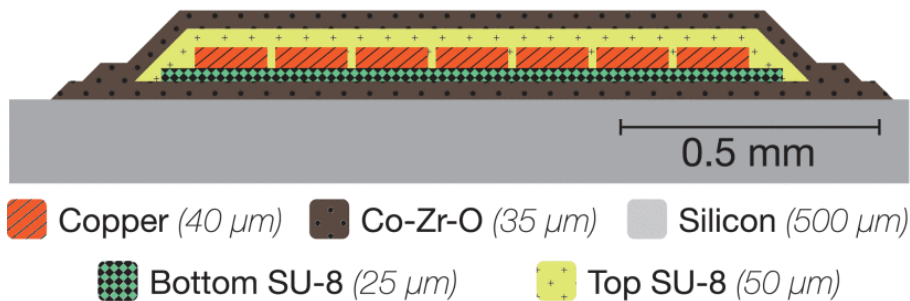


Applications of Granular Metals

Magnetic Materials

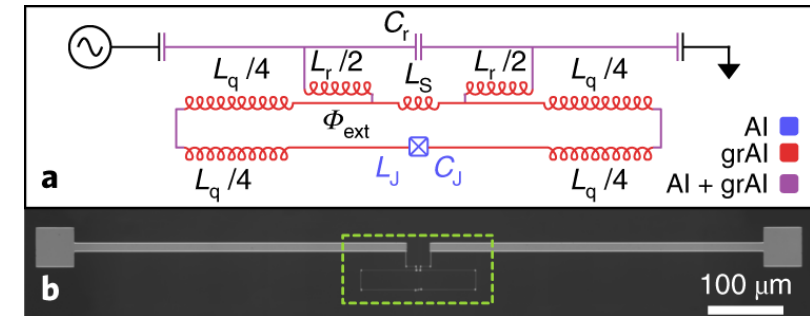


S. H. Liou and C. L. Chien; Granular metal films as recording media. *Appl. Phys. Lett.* **52**, 512 (1988)



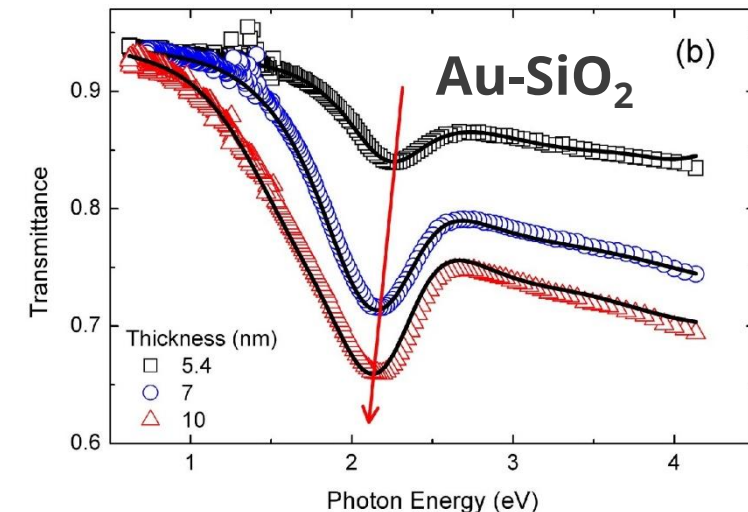
D. V. Harburg et al., *IEEE Journal of Emerging and Selected Topics in Power Electronics* **6**, 1280 (2018)

Superconducting Circuits



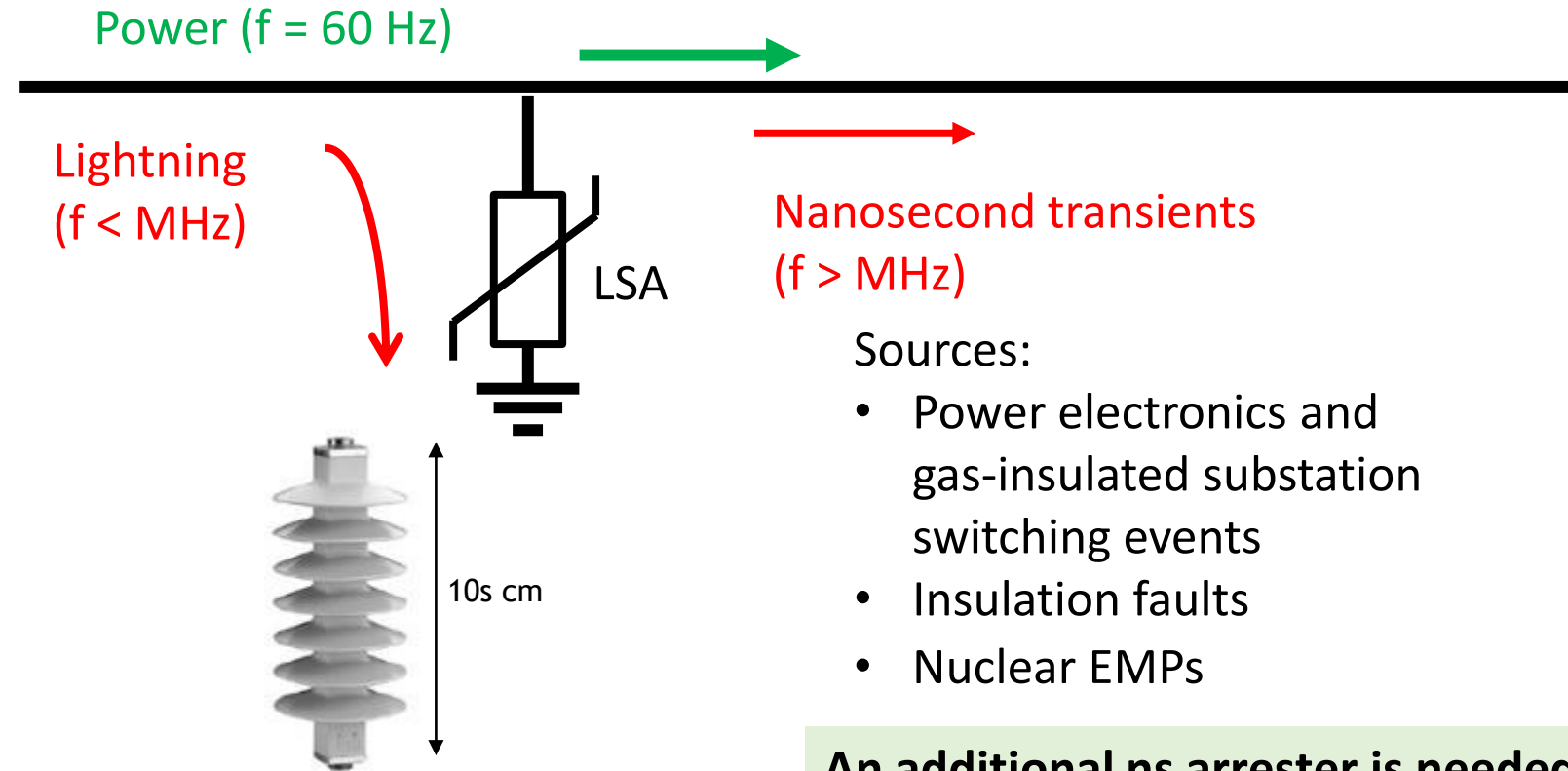
L. Grünhaupt et al., *Nat. Mater.* **18**, 816 (2019)

Plasmonics



H. Bakkali, et al. *Applied Surface Science* **405**, 240 (2017)

Nanosecond high-voltage transients threaten electrical grid reliability



Lightning surge arresters' (LSAs) response time is $\sim 100 \text{ ns}$

vulnerable infrastructure



Sources:

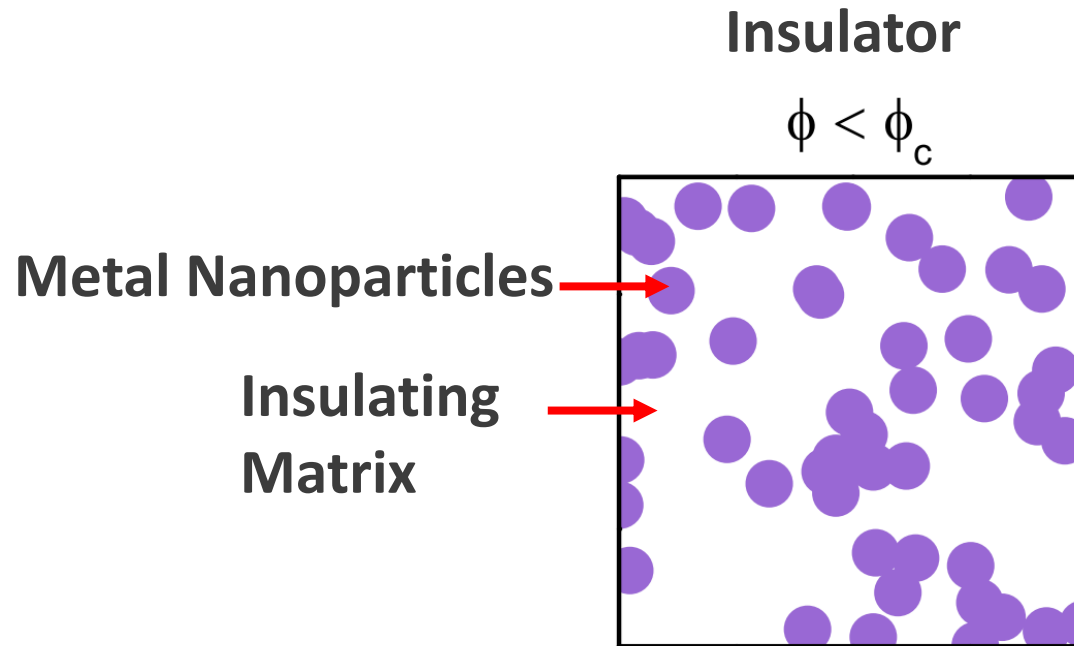
- Power electronics and gas-insulated substation switching events
- Insulation faults
- Nuclear EMPs

An additional ns arrester is needed with

- High breakdown strength for compact devices
- Low conductivity, σ , at grid voltages and frequencies
- High σ at MHz/GHz frequencies and with overvoltages
- High thermal stability
- Large current carrying capacity ($>1 \text{ kA/cm}^2$)



Granular metals are promising for ultrafast grid protection.



Grimaldi, Phys. Rev. B **89**, 214201 (2014)

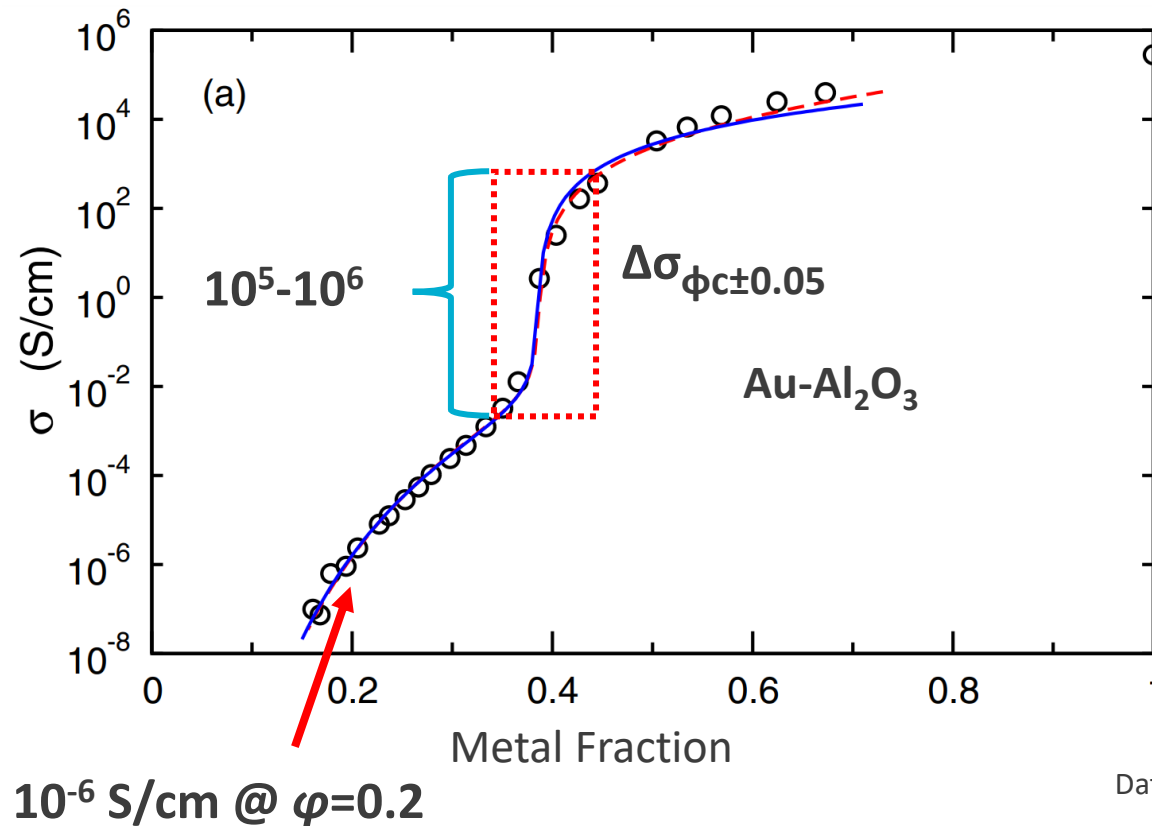
Below φ_c conduction occurs via electron tunneling and capacitive transport.

Conduction from electron tunneling increases at higher electric fields.

Conduction from capacitive transport increases at higher frequencies.



GMs have desired low DC conductivity.



Data: Abeles et al. Adv. in Phys. **24**, 407 (1975)

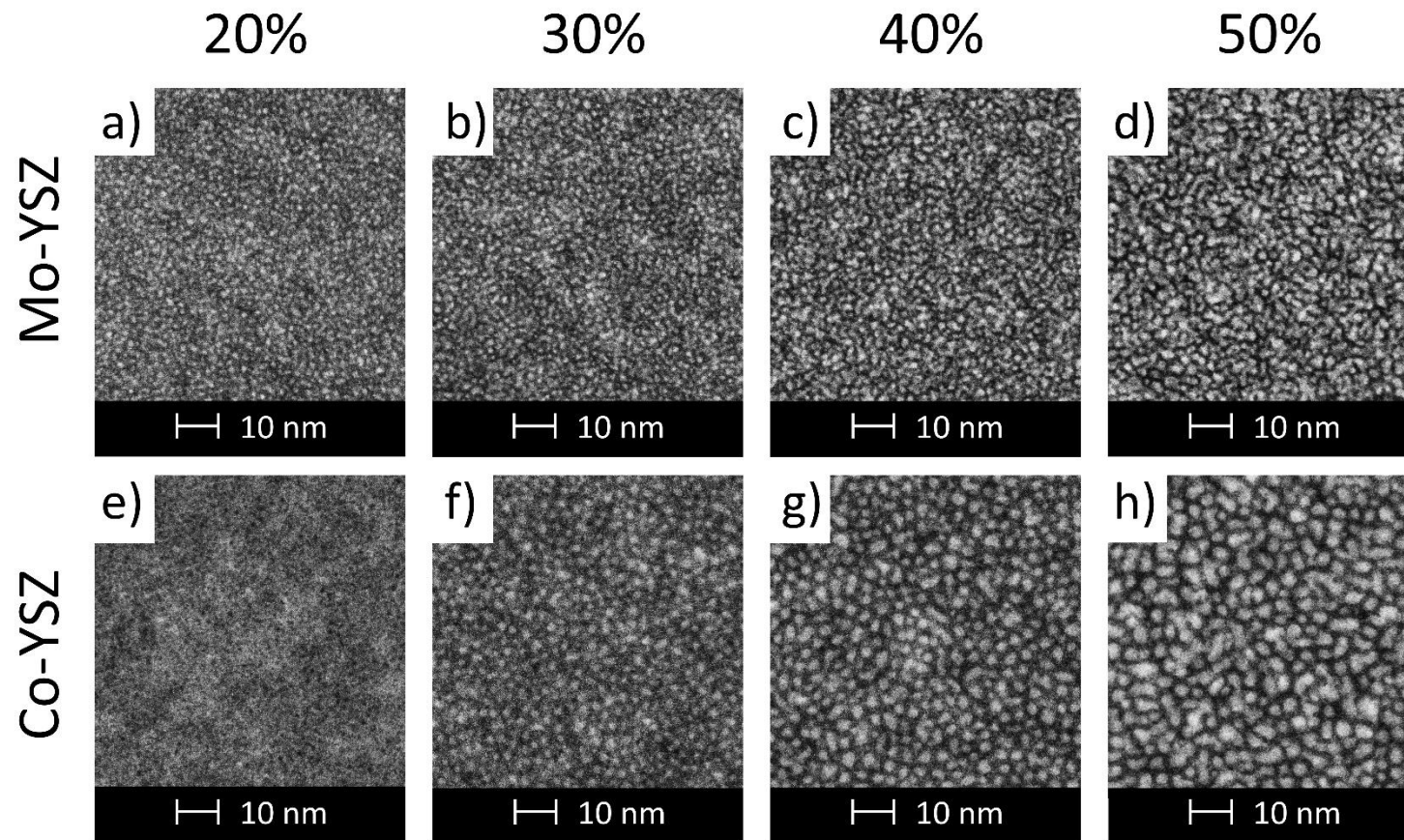
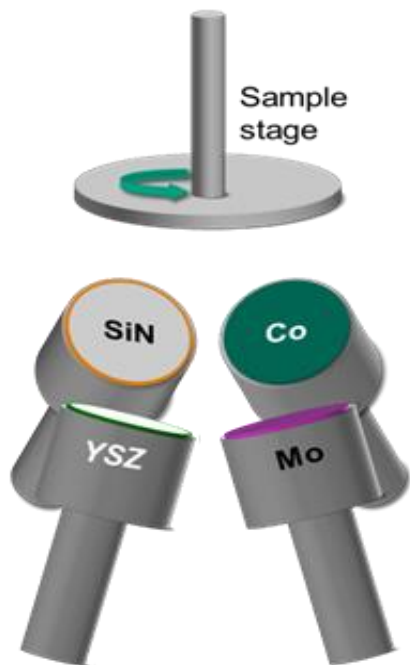
Figures: Grimaldi, Phys. Rev. B **89**, 214201 (2014)

Conductivities of $<10^{-5}$ S/cm are desired to reduce leakage currents.



Co-YSZ and Mo-YSZ synthesized by RF co-sputtering in Ar

Volumetric Metal Fraction

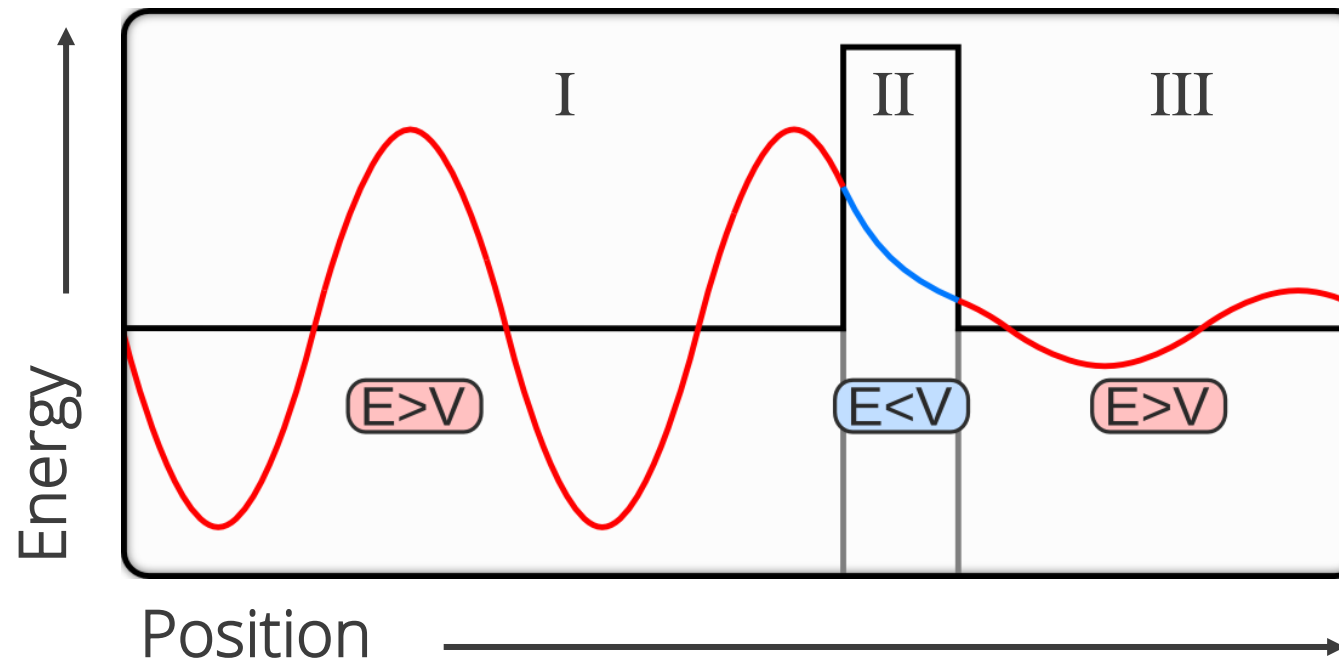


Metal island diameters between 1-3 nm.

Particle separation distances are ~0.2 - 0.6 nm



Quantum Tunneling



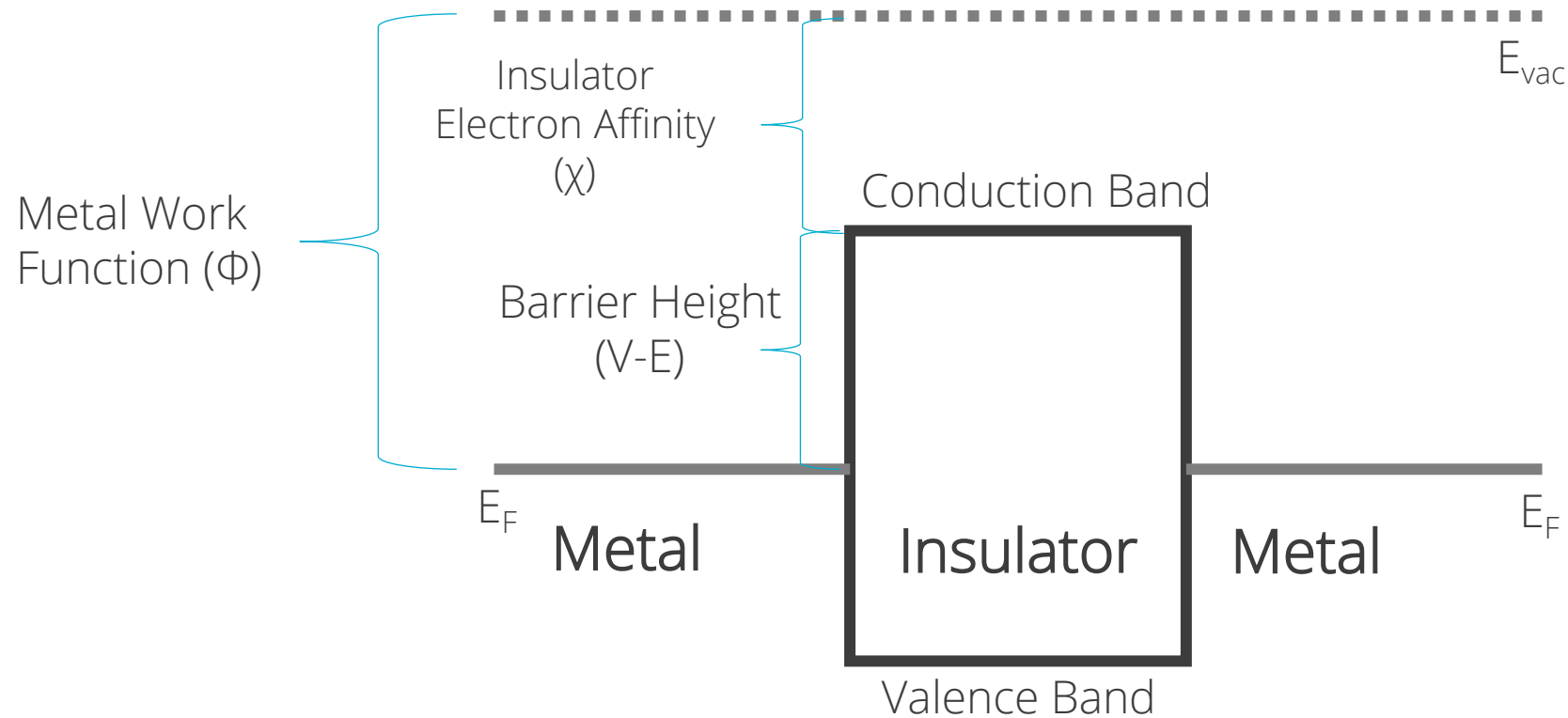
$$\Psi(x) = \begin{cases} Ae^{ikx} + Be^{-ikx} & , \text{ I} \\ Ce^{\kappa x} + De^{-\kappa x} & , \text{ II} \\ Fe^{ikx} & , \text{ III} \end{cases}$$

Tunneling Probability Decay Length

$$\kappa = \sqrt{\frac{2m(V-E)}{\hbar^2}}$$



Quantum tunneling in granular metals

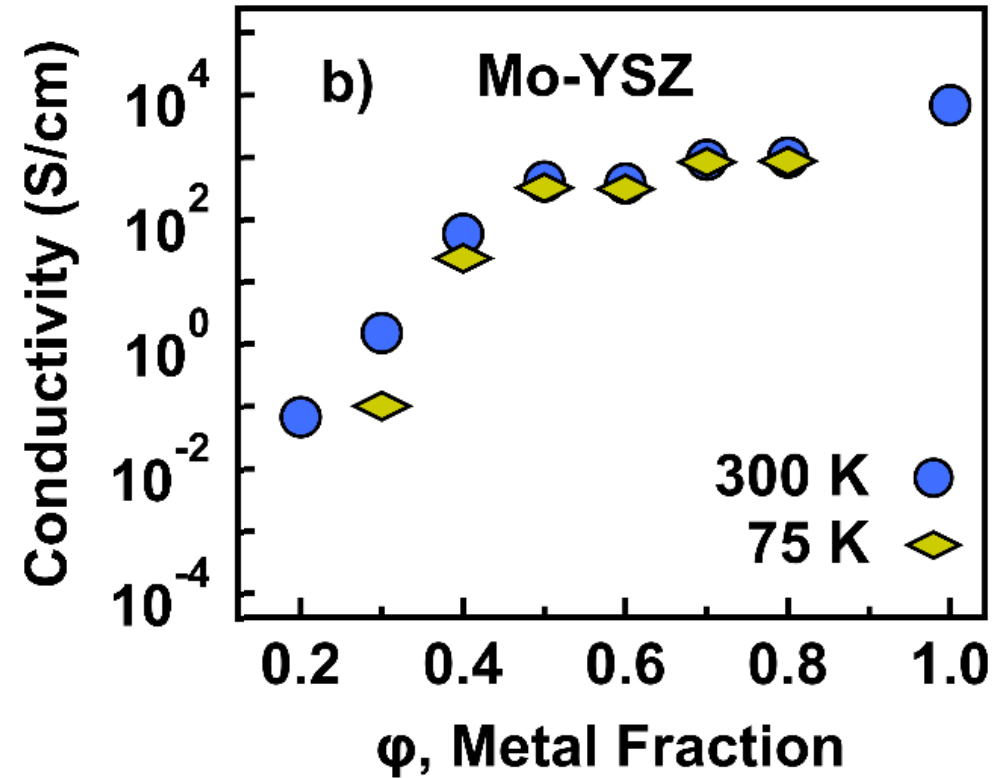
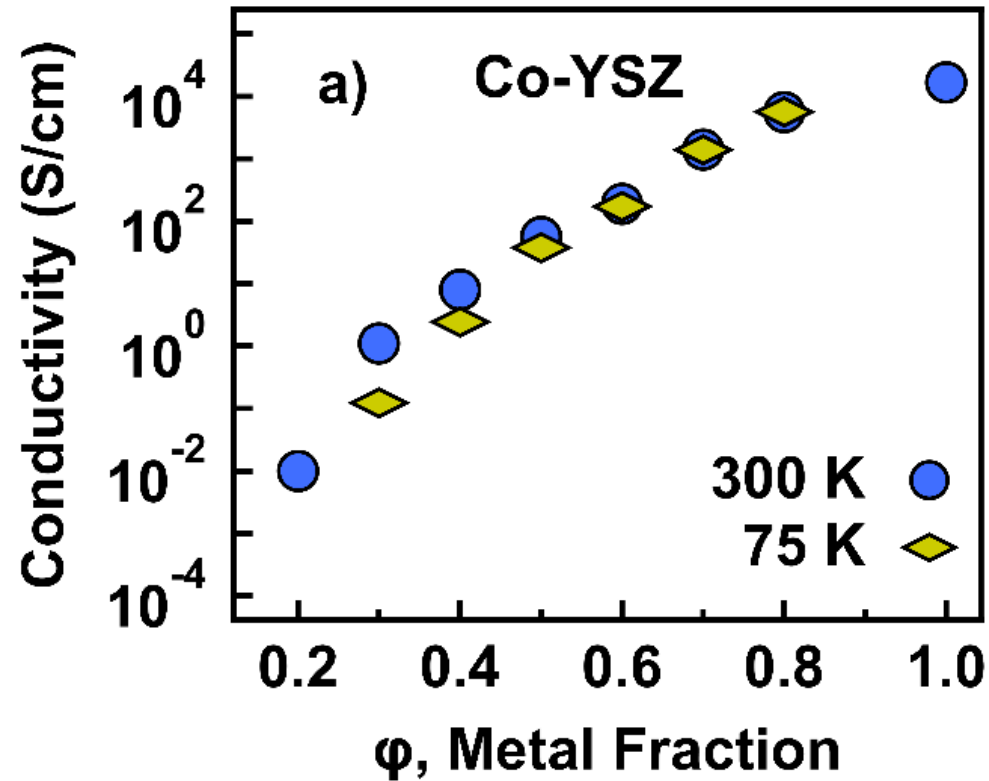


Tunneling Probability Decay Length

$$\kappa = \sqrt{\frac{2m(V-E)}{\hbar^2}} = \sqrt{\frac{2m(\Phi-\chi)}{\hbar^2}} = 0.1 - 0.2 \text{ nm}$$



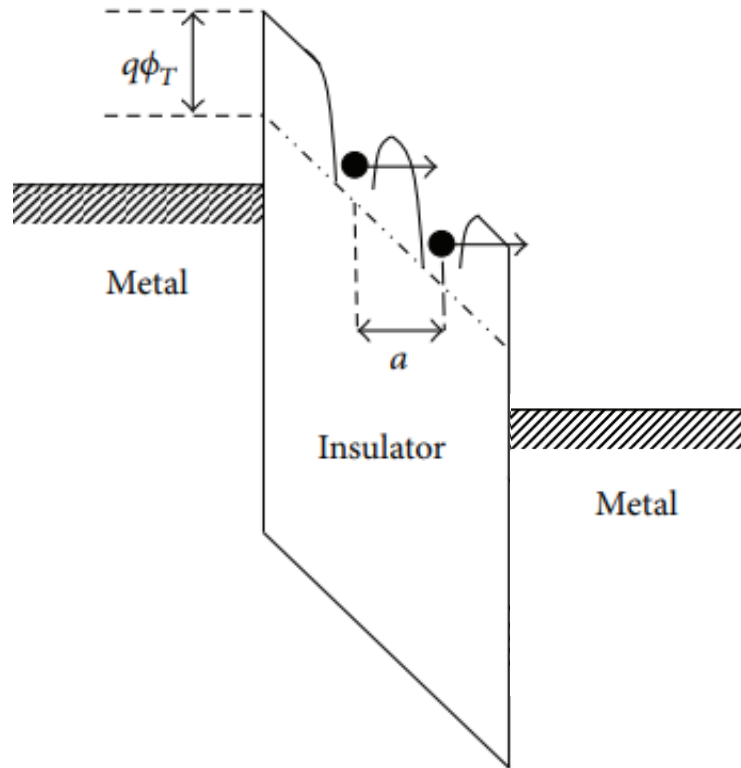
Co-YSZ and Mo-YSZ have high DC conductivities.





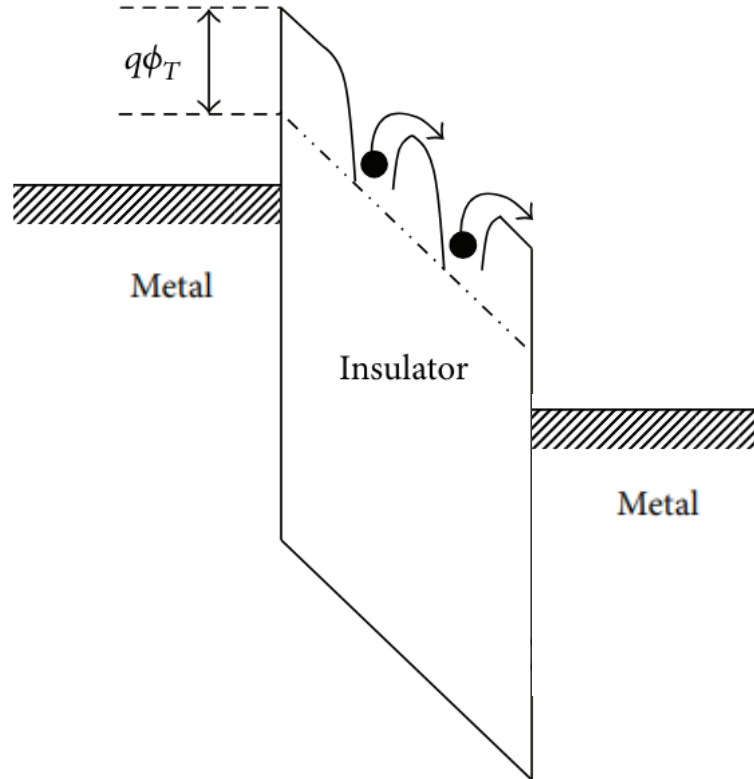
Potential tunneling mechanisms

Hopping Conduction



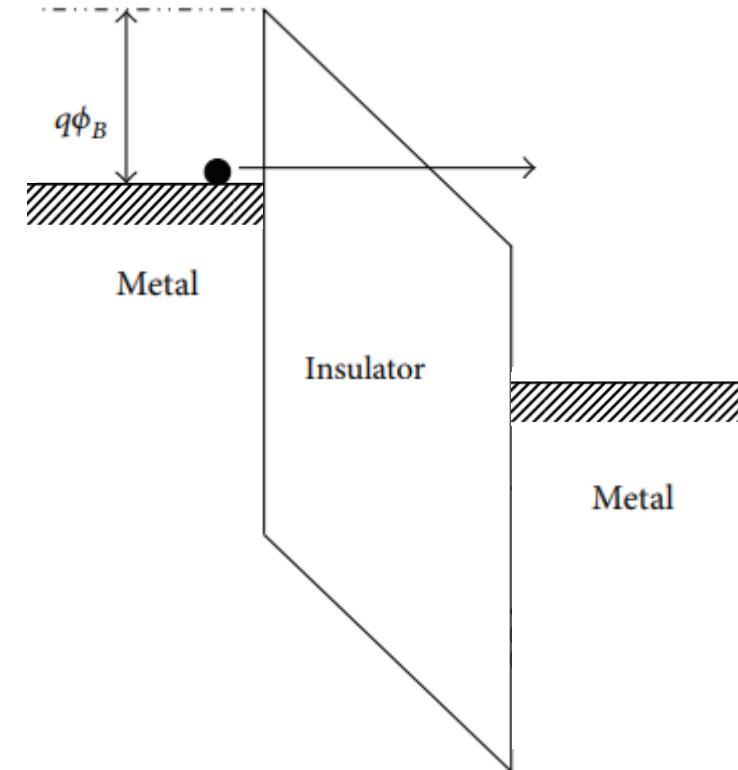
$$\sigma \propto \exp(-2\sqrt{E_A/k_B T})$$

Poole-Frenkel Emission



$$\sigma \propto \exp \left[(q/k_B T) \sqrt{qE/\epsilon_0 \epsilon_r} \right]$$

Fowler-Nordheim Tunneling

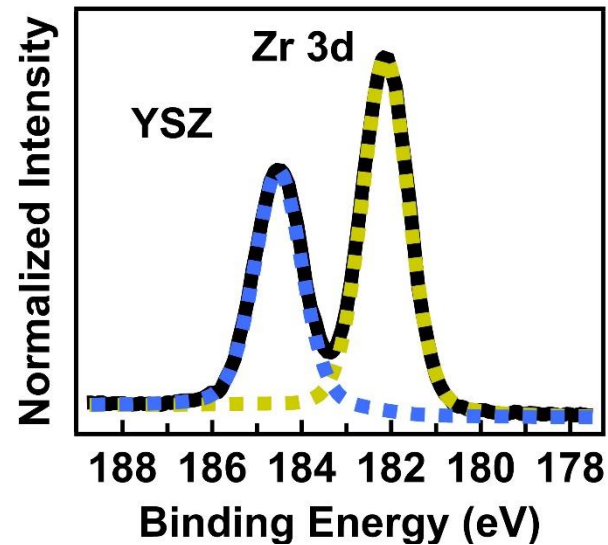


$$\sigma \propto E^2 \exp(E_0/E)$$

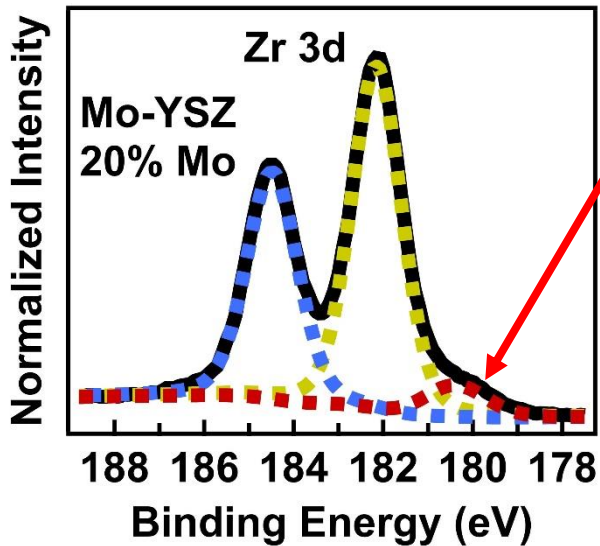
Conductivity depends on defect density, temperature and electric field.



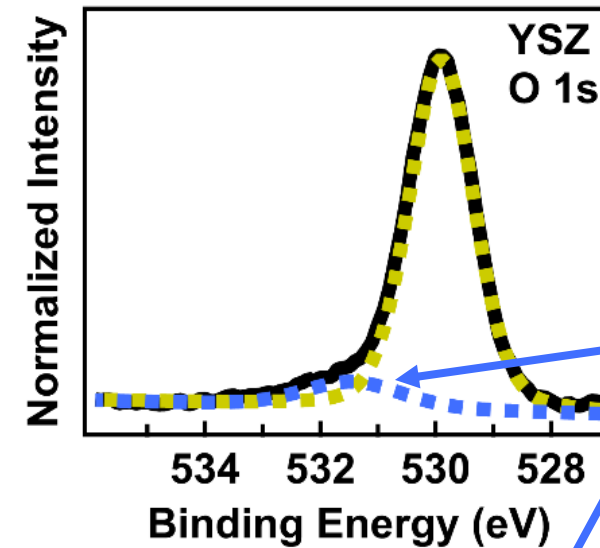
X-ray photoemission spectroscopy shows metal-oxide formation



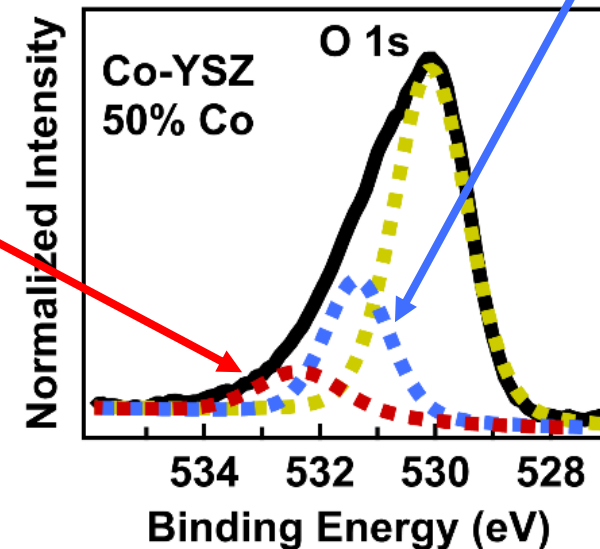
Zr²⁺ from
oxygen
vacancies



Metal-oxide
interface
states

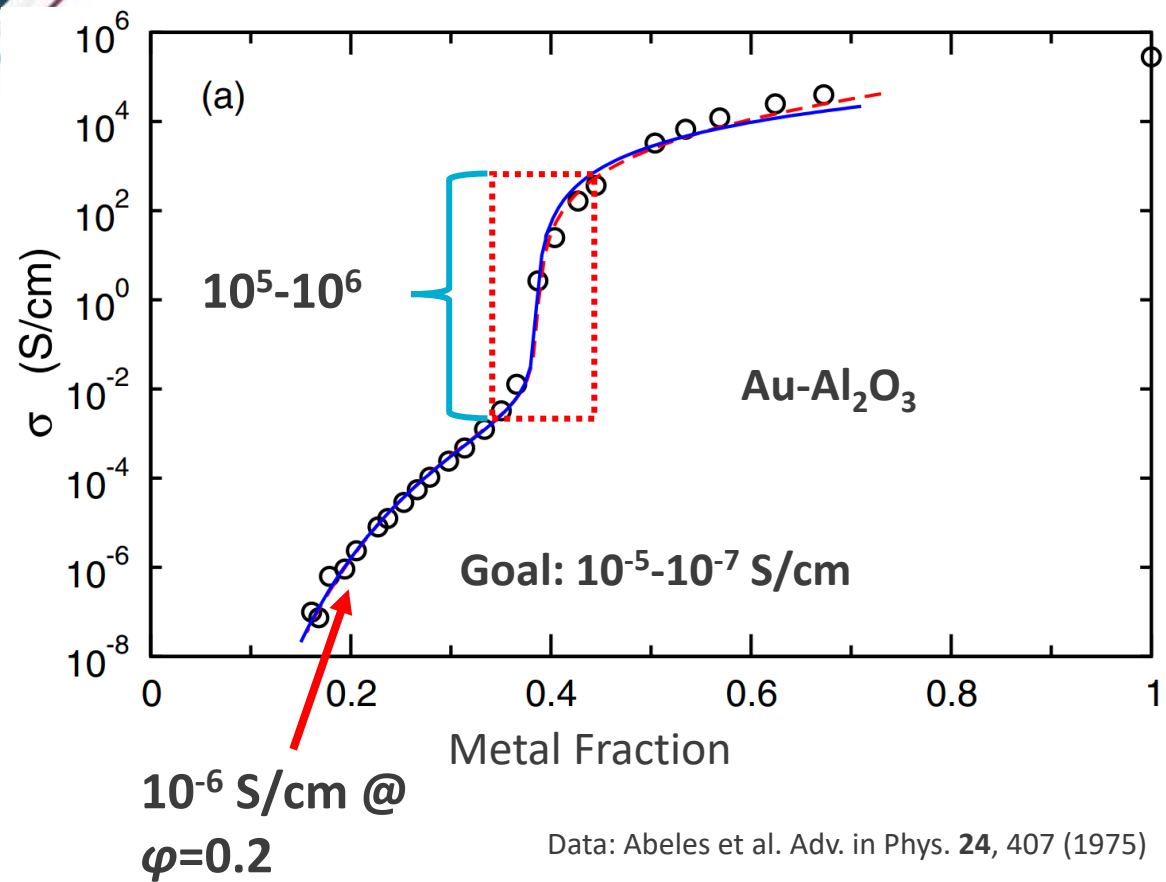


Surface
oxygen
in YSZ



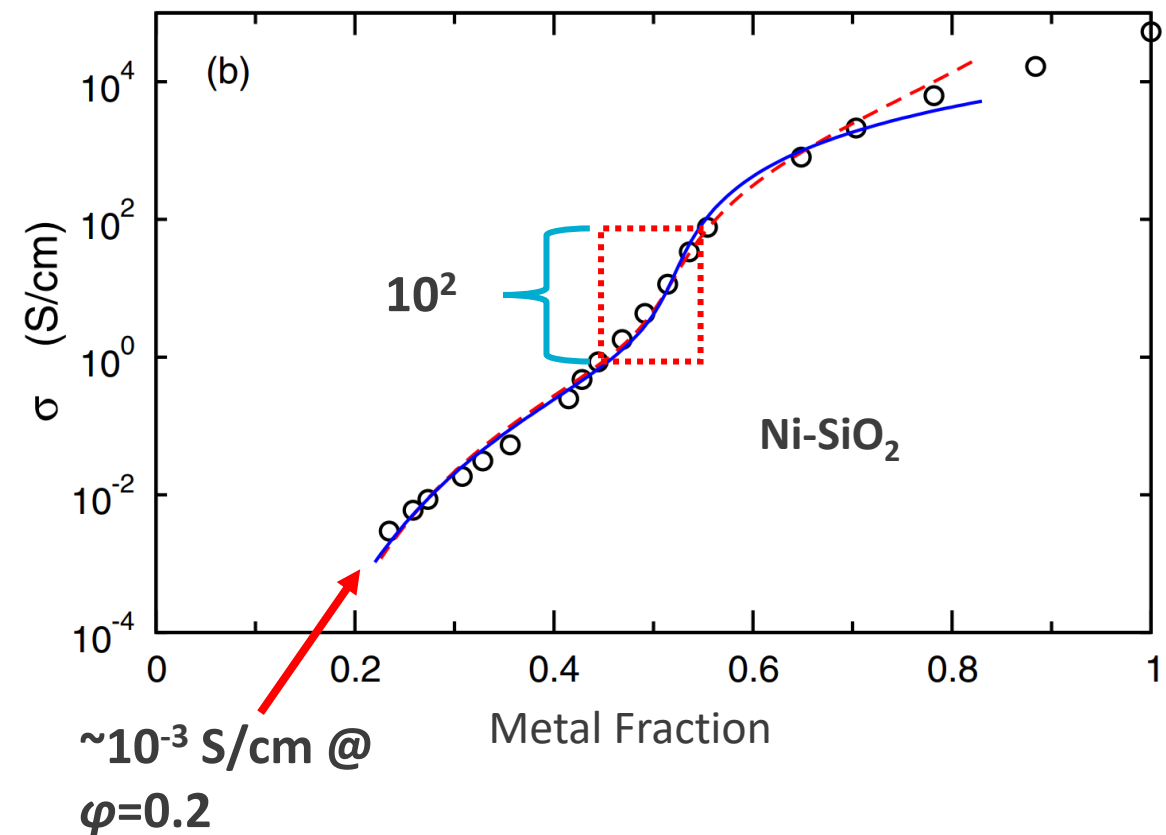


Noble Metal GMs have desired low DC conductivity.



Data: Abeles et al. Adv. in Phys. **24**, 407 (1975)

Figures: Grimaldi, Phys. Rev. B **89**, 214201 (2014)



Noble metals are expensive and have lower than desired thermal stabilities.

Nearly all granular metals utilize oxide insulators.



Metal-oxide formation reduces GM performance.

Reference	Metal	Insulator	$\Delta\sigma_{\phi_{c\pm 0.05}}$
This work	Mo	YSZ	10^1
This work	Co	YSZ	10^1
Stogneř ¹	Co	Al_2O_n	10^2
Barzilai ³	Co	SiO_2	10^2
Zhu ⁴	Fe	Al_2O_3	10^2
Aronzon ⁵	Fe	SiO_2	10^2
Honda ⁶	Fe	SiO_2	10^3
Gittleman ⁷	Ni	SiO_2	10^2
Toker ⁸	Ni	SiO_2	10^2
Abeles ⁹	Ni	SiO_2	10^2
Milner ¹⁰	Ni	SiO_2	10^4
Abeles ¹¹	W	Al_2O_3	10^2
Wei ¹²	Ag	SnO_2	10^1
Balberg ¹³	Ag	Al_2O_3	10^2
Cohen ¹⁴	Ag	SiO_2	10^4
Priestley ¹⁵	Ag	SiO_2	10^5
Abeles ⁹	Au	Al_2O_3	10^6
Cohen ¹⁴	Au	SiO_2	10^4
McAlister ¹⁶	Au	SiO_2	10^8

Conductivity change across percolation threshold.

Non-noble metals typically 10^2 - 10^3

Noble metals typically $\geq 10^4$

¹Stogneř et al. Phys. Solid State **49**, 164 (2007)

²Niklasson et al. J. Appl. Phys. **55**, 3382 (1984)

³Barzilai et al. Phys. Rev. B **23**, 1809 (1981)

⁴Zhu et al. Phys. Rev. B **60**, 11918 (1999)

⁵Aronzon et al. Phys. Solid State **41**, 857 (1999)

⁶Honda et al. Phys. Rev. B **56**, 14566 (1997)

⁷Gittleman et al., Phys. Rev. B **5**, 3609 (1972)

⁸Toker et al. Phys. Rev. B **68**, 041403(R) (2003)

⁹Abeles et al. Adv. in Phys. **24**, 407 (1975)

¹⁰Milner et al. Phys. Rev. Lett. **76**, 475 (1996)

¹¹Abeles et al. Phys. Rev. Lett. **35**, 247 (1975)

¹²Wei et al. Appl. Phys. Lett. **102**, 131911 (2013)

¹³Balberg et al. Eur. Phys. J. B **86**, 428 (2013)

¹⁴Cohen et al., Phys. Rev. B **8**, 3689 (1973)

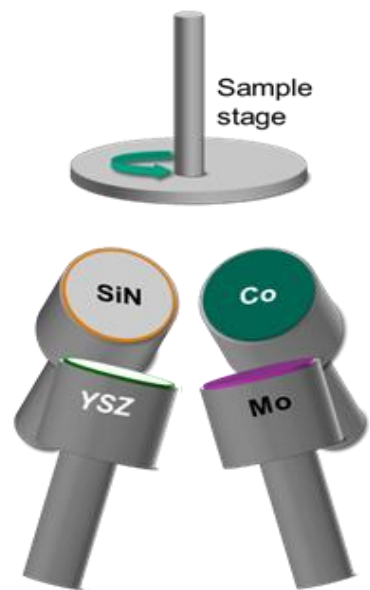
¹⁵Priestley et al. Phys. Rev. B **12**, 2121 (1975)

¹⁶McAlister et al. J. Phys. C: Solid State Phys. **17**, L751 (1984)

S.J. Gilbert et al., J. Phys. Condens. Matter **34**, 204007 (2022)



Co-SiN_x and Mo-SiN_x GMs were synthesized by RF co-sputtering.



Mo-SiN_x

Co-SiN_x

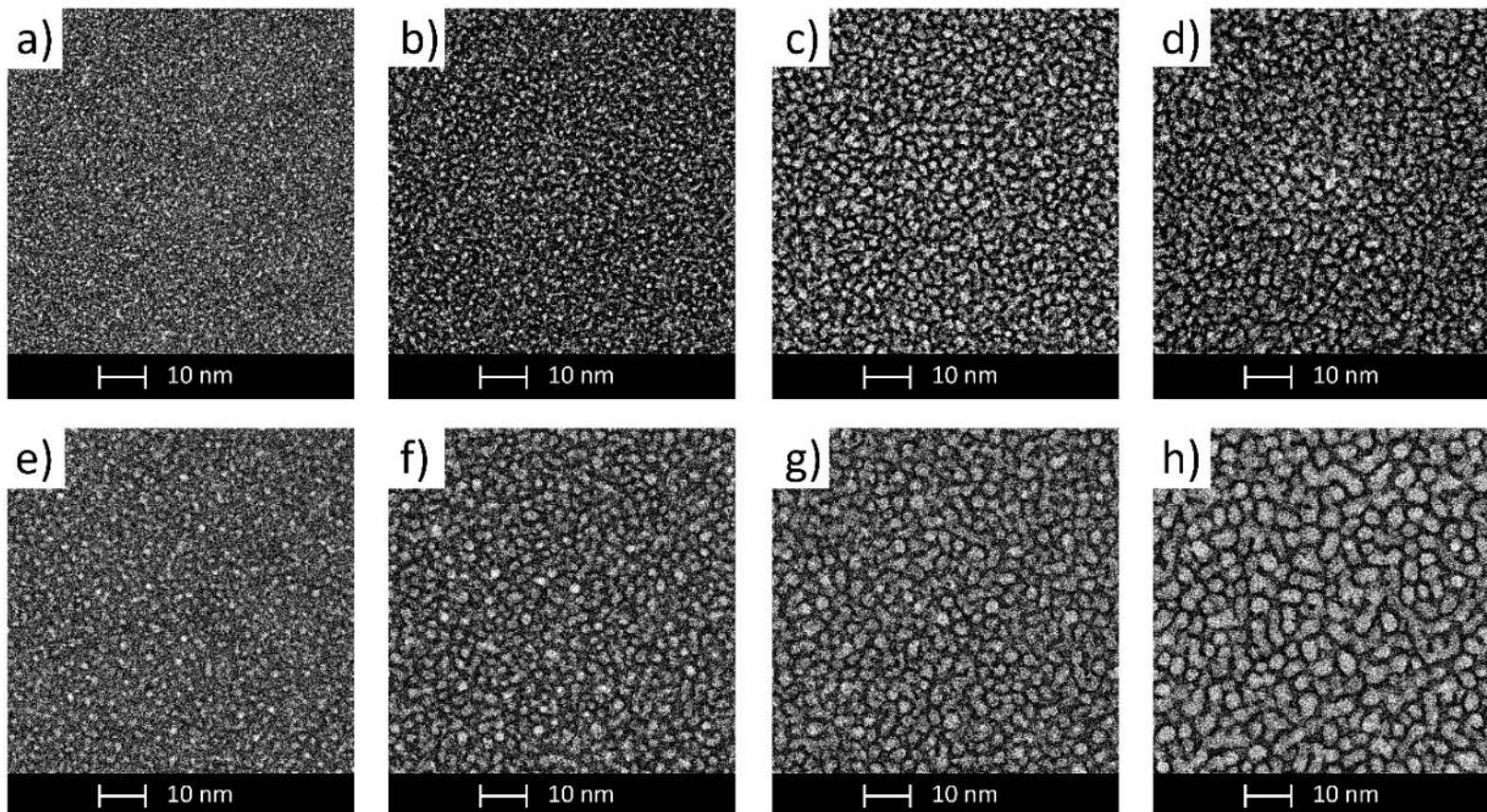
Volumetric Metal Fraction

20%

30%

40%

50%

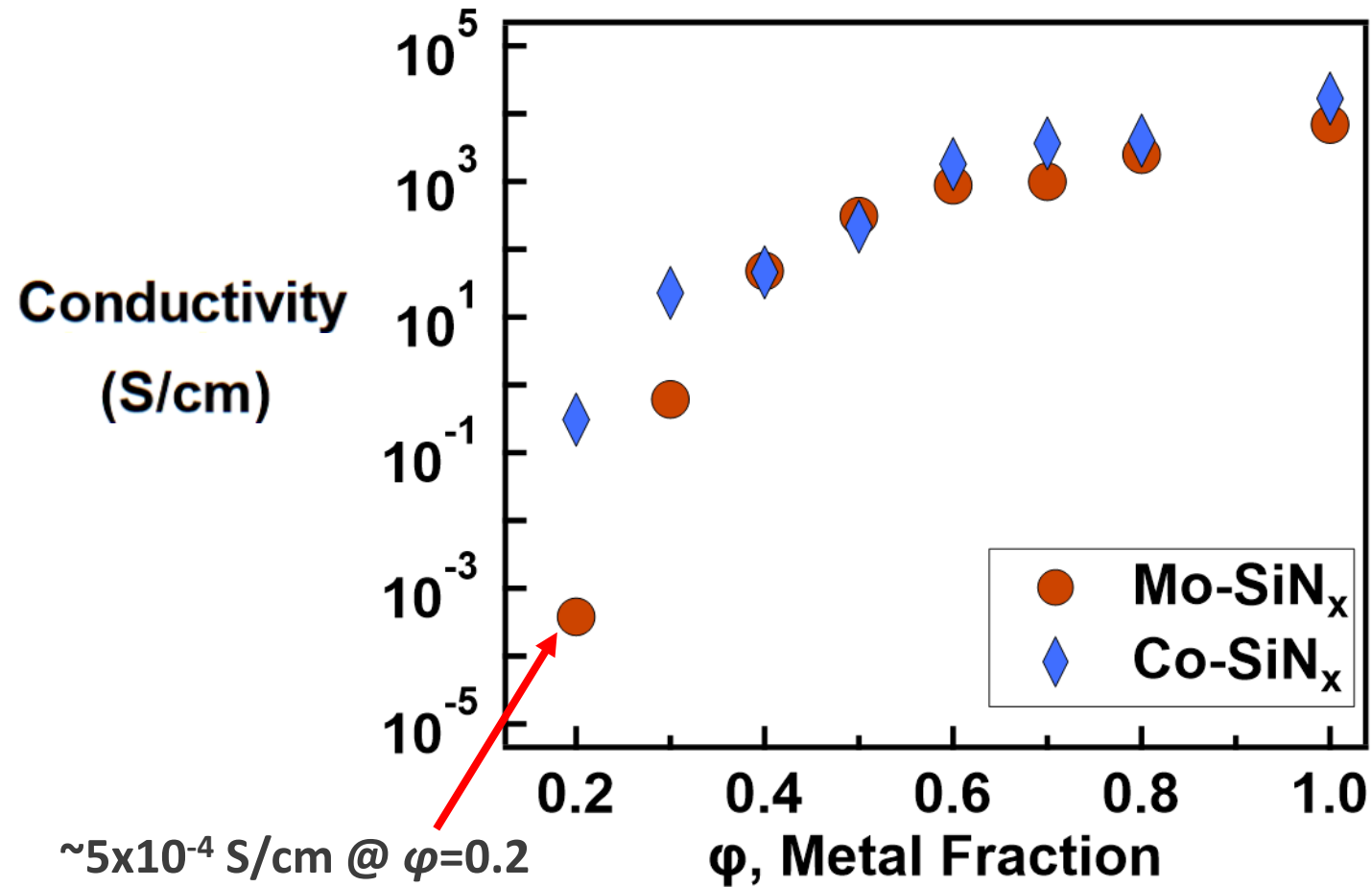


S.J. Gilbert et al., Nanotechnology, **34**, 415706 (2023)

Nanoparticle diameters and separations are similar to YSZ GMs.



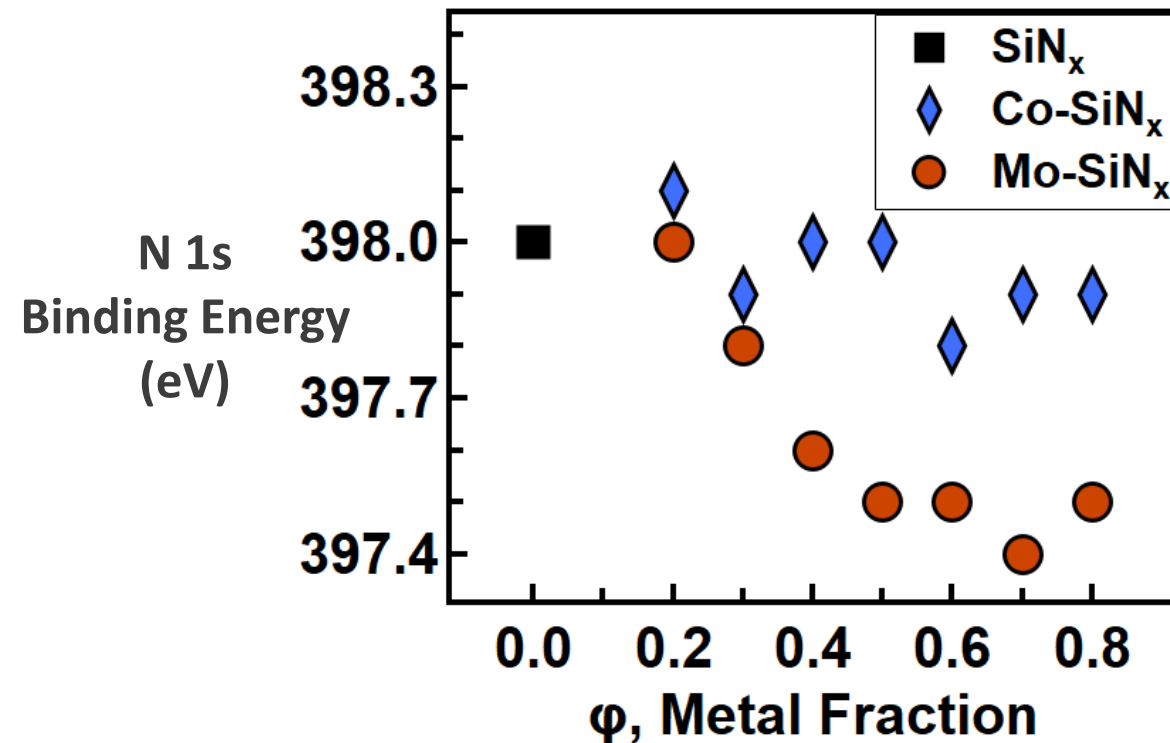
Conductivity still too high for electrical grid integration.



Target conductivity is 10^{-5} - 10^{-8} S/cm



Mo-SiN_x exhibits Mo-nitride formation.



S.J. Gilbert et al., Nanotechnology, **34**, 415706 (2023)

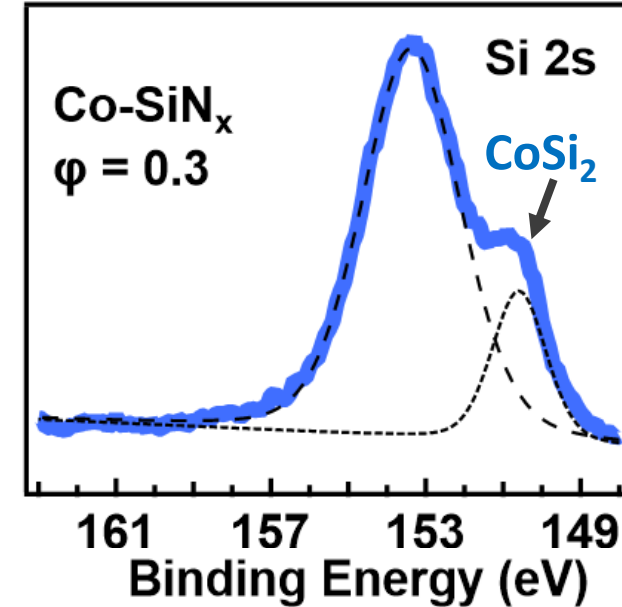
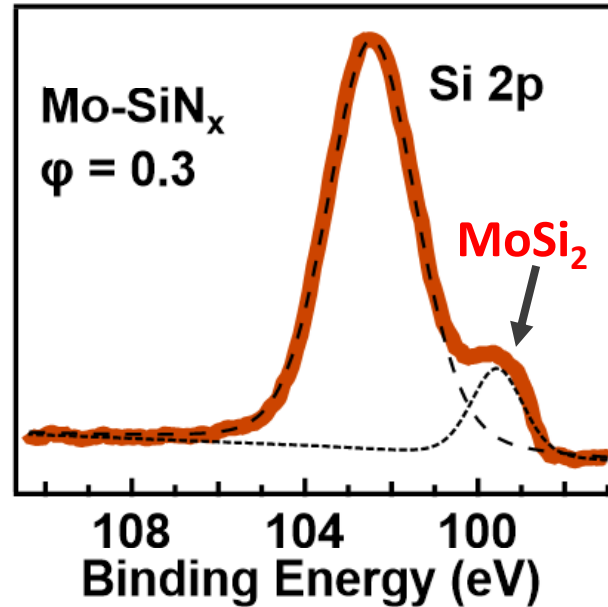
Group	Compound	ΔH (kJ*mol ⁻¹ *atom ⁻¹)	Reference
Mo-Nitrides	Mo ₂ N	-41	1
	MoN	-51	1
Co-Nitrides	Co ₄ N	+3	2
	Co ₂ N	-9	1
	CoN	0	1

1. A. K. Niessen et al., Journal of the Less Common Metals **82**, 75-80 (1981).
2. I. K. Milad et al., Catalysis Letters **52**, 113-119 (1998).

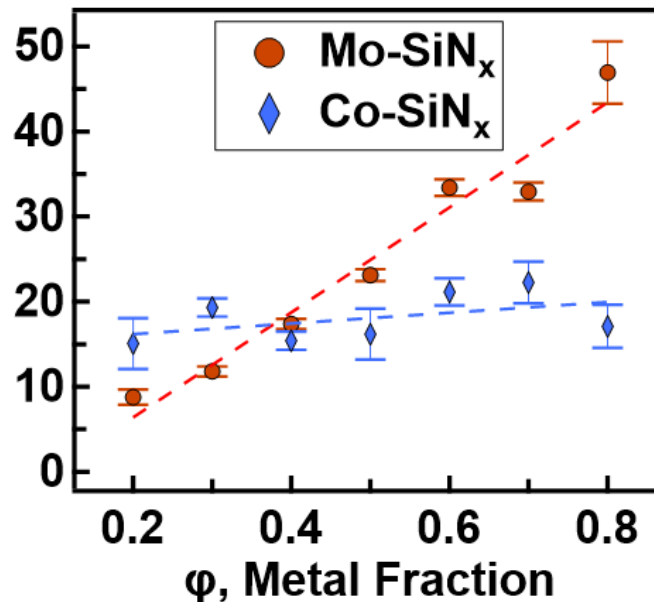


Nitrogen vacancies cause metal-silicide formation and increase conductivity.

Normalized
Intensity



% of Si in
metal-silicides



Target	Sputtering gas	$\rho_{(300K)}$ (Ω cm)
β -Si ₃ N ₄	100%Ar	1.7×10^{10}
	80%Ar-20N ₂	1.1×10^{11}
	50%Ar-50N ₂	3.4×10^{14}
	20%Ar-80N ₂	1.3×10^{13}
	100N ₂	6.2×10^{12}

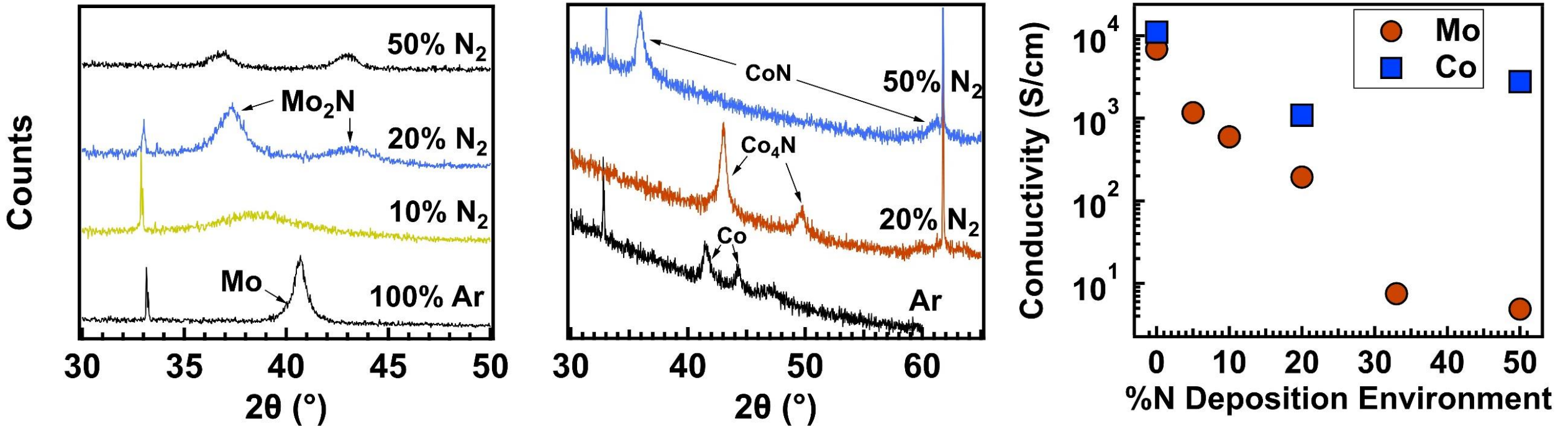
Vila et al. Thin Solid Films **459**, 195 (2004)

Insulator can be repaired by
depositing in Ar/N₂.



Sputtering metals in N_2 results in metal-nitrides.

X-ray diffraction



Selected environments

Mo-SiN_x: 10% N_2

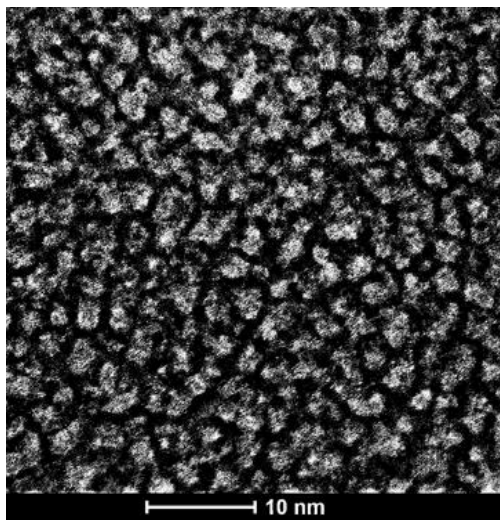
Co-SiN_x: 50% N_2



Deposition in N₂ Reduces Nanoparticle Size

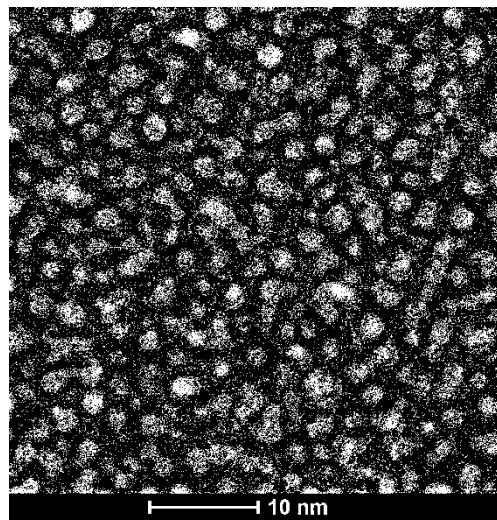
Mo-SiN_x ($\phi=0.5$)

100% Ar



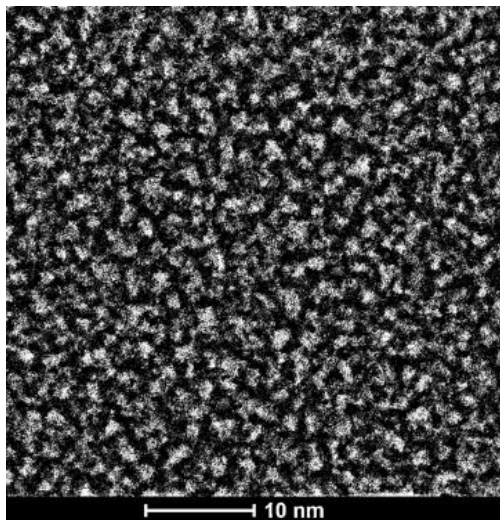
Co-SiN_x ($\phi=0.3$)

100% Ar



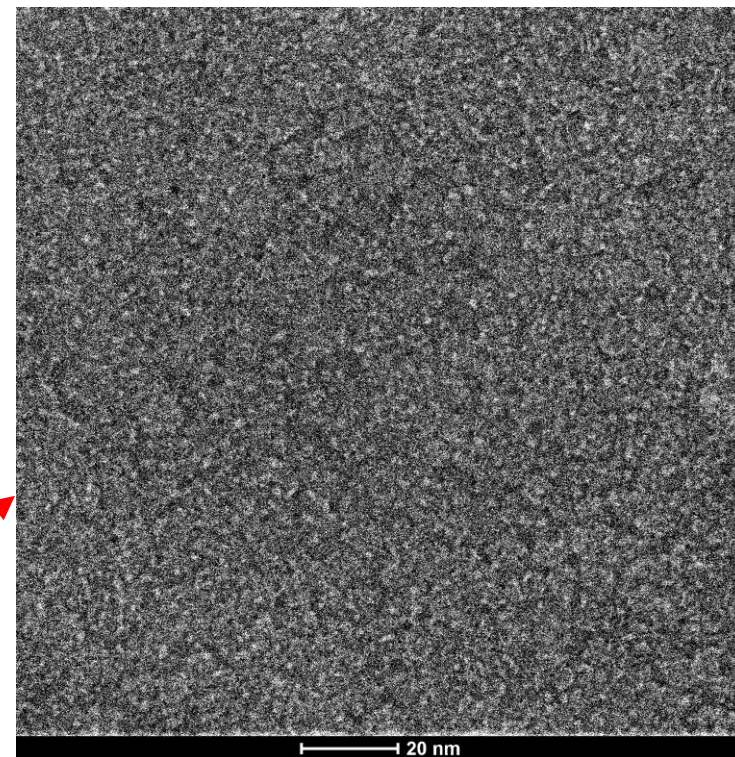
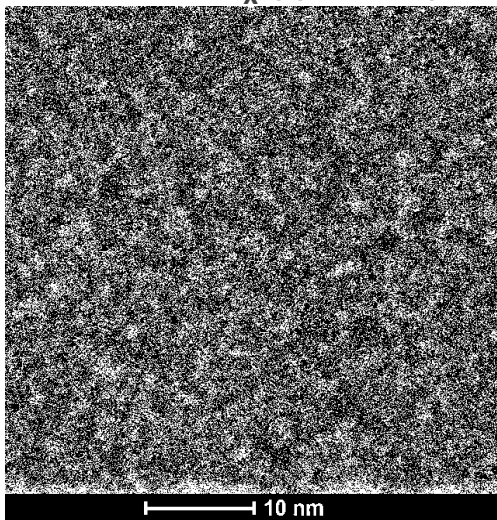
Mo-SiN_x ($\phi=0.5$)

10% N₂



Co-SiN_x ($\phi=0.35$)

50% N₂

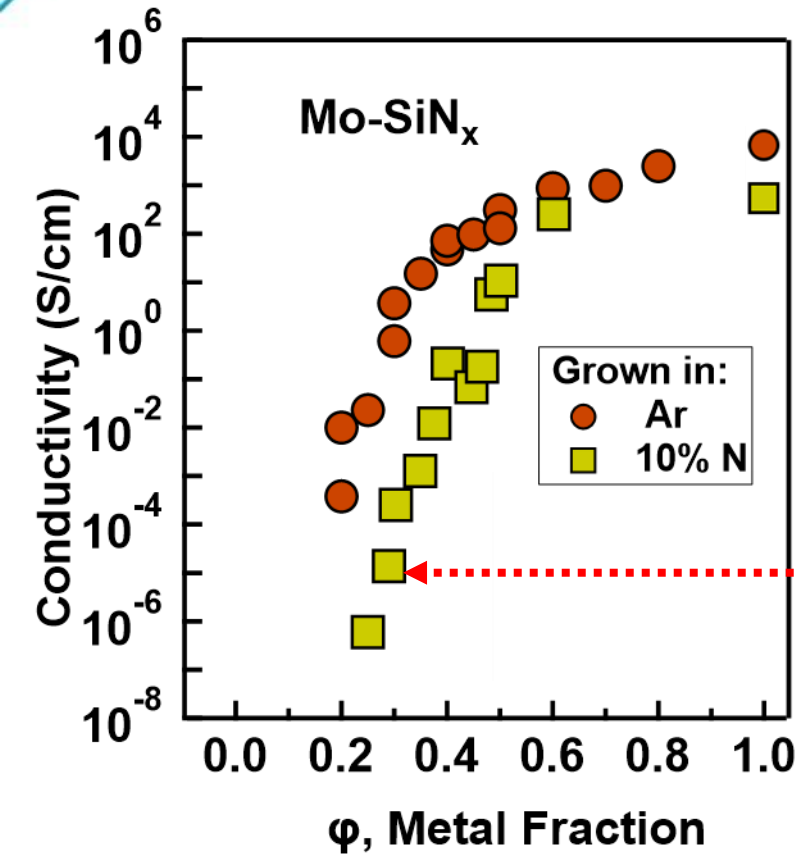


M. McGarry et al., submitted

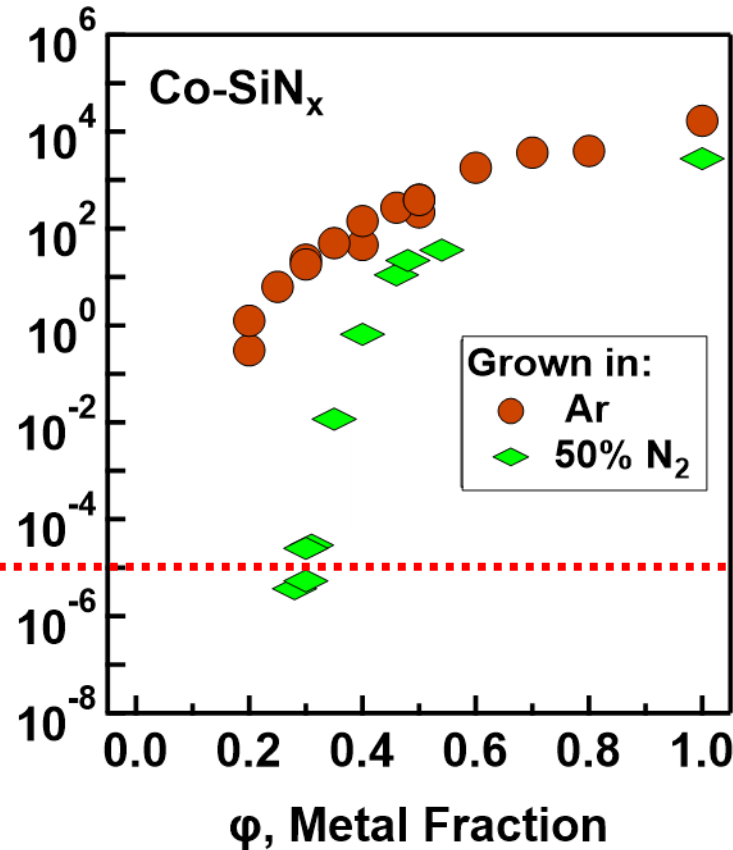
S.J. Gilbert et al., in progress



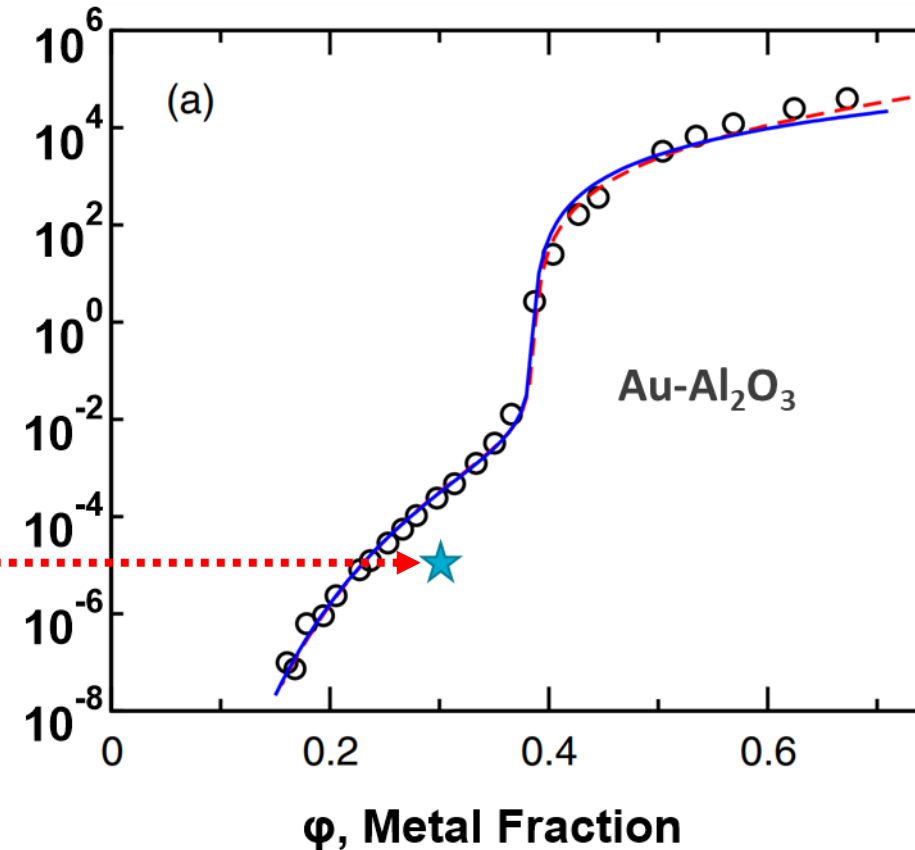
Significant insulator improvements when deposited N₂



M. McGarry et al., submitted



S.J. Gilbert et al., in progress



Data: Abeles et al. Adv. in Phys. **24**, 407 (1975)

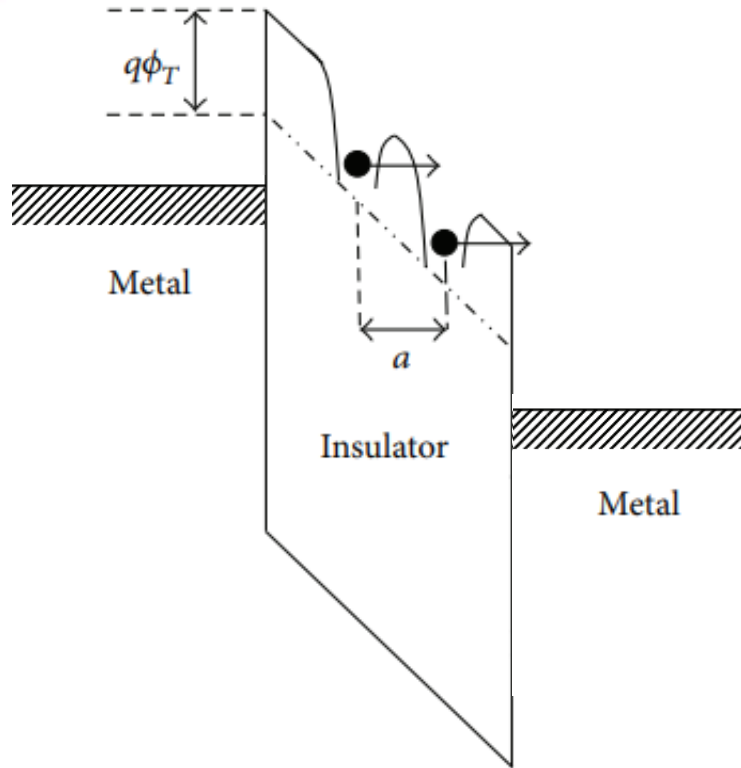
Figure: Grimaldi, Phys. Rev. B **89**, 214201 (2014)

Low conductivities previously only seen with noble metals.

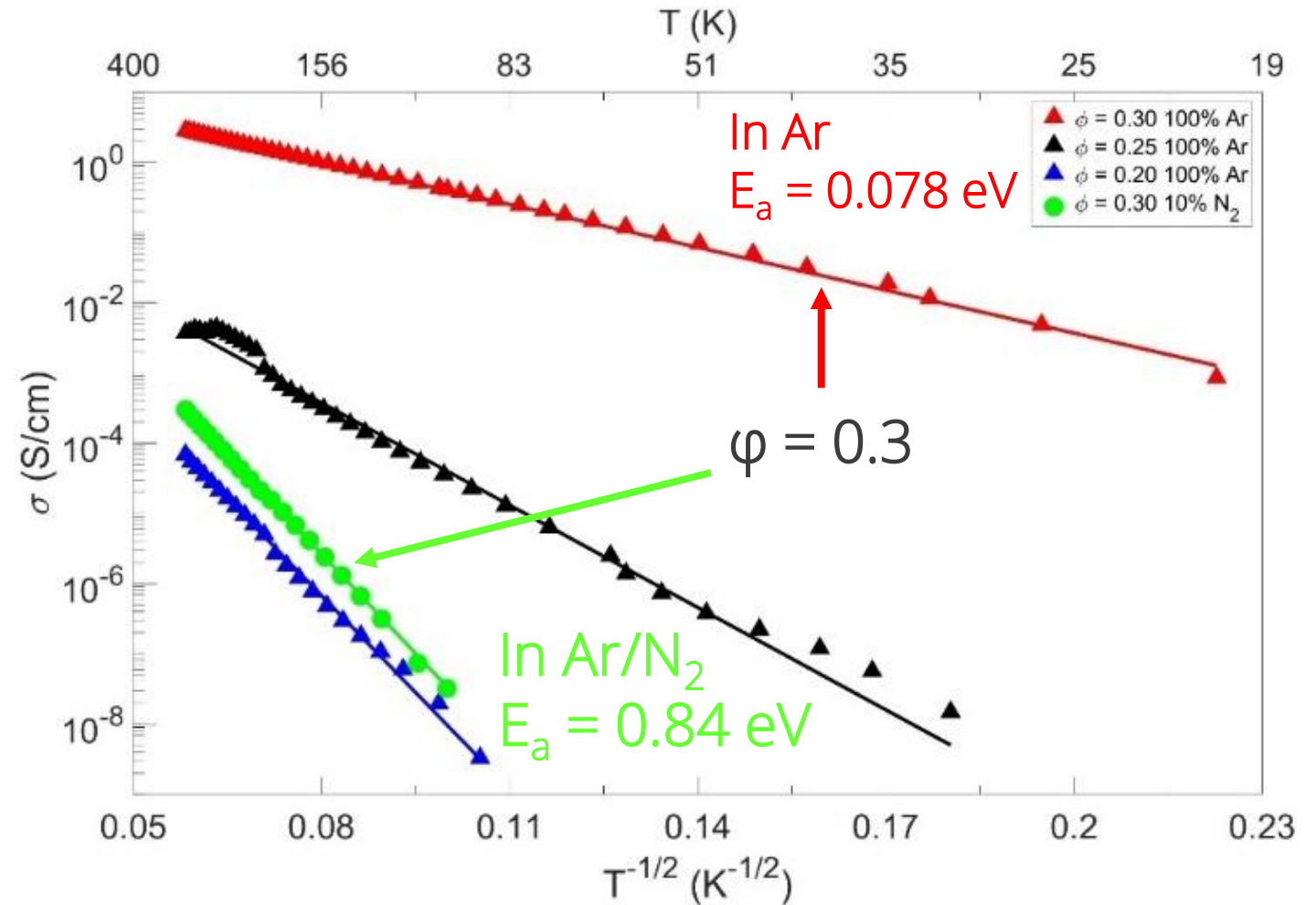


Deposition in N₂ greatly increases activation energy

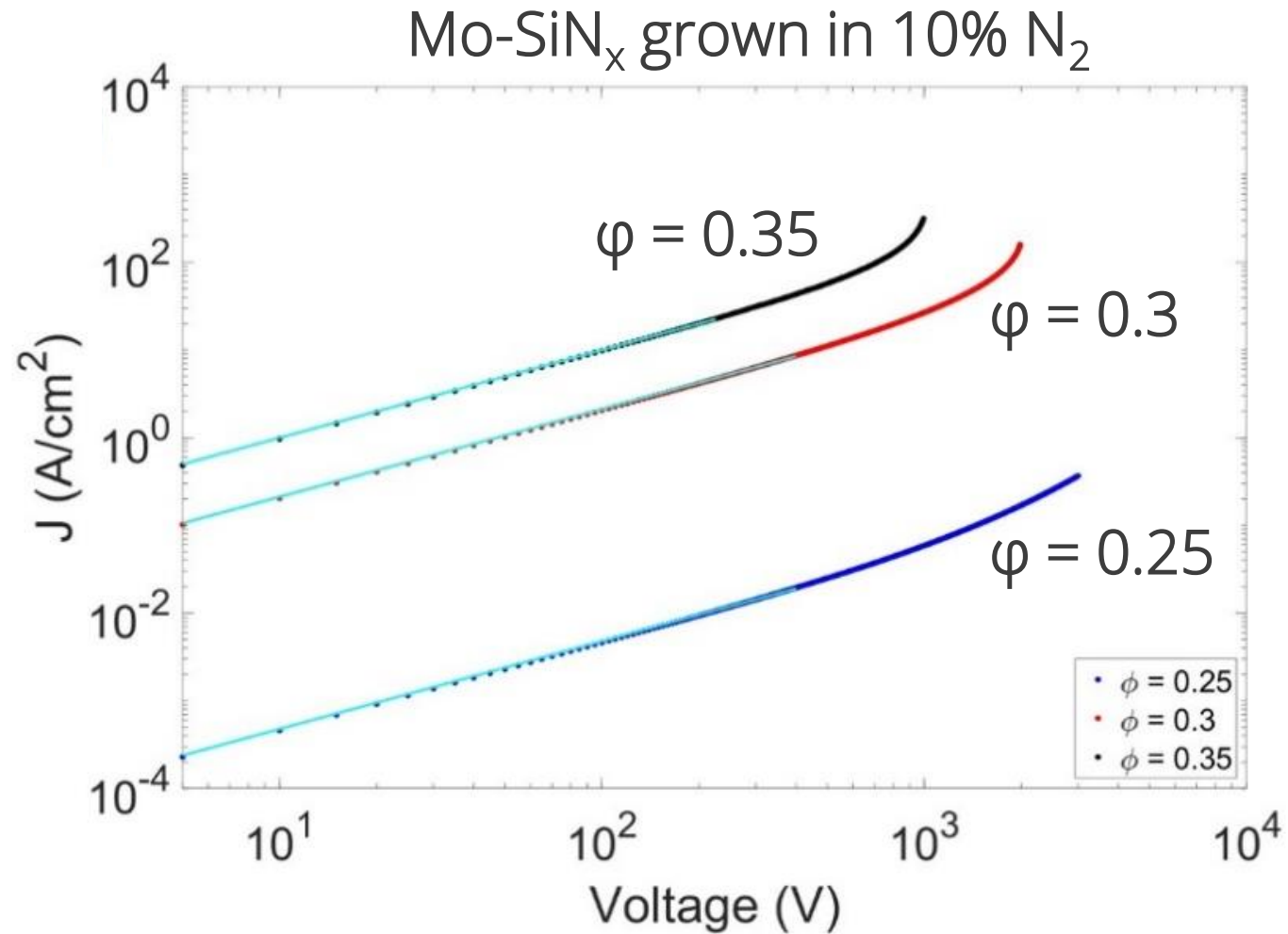
Hopping Conduction



$$\sigma \propto \exp(-2\sqrt{E_A/k_B T})$$



Field enhanced tunneling is observed at higher electric fields



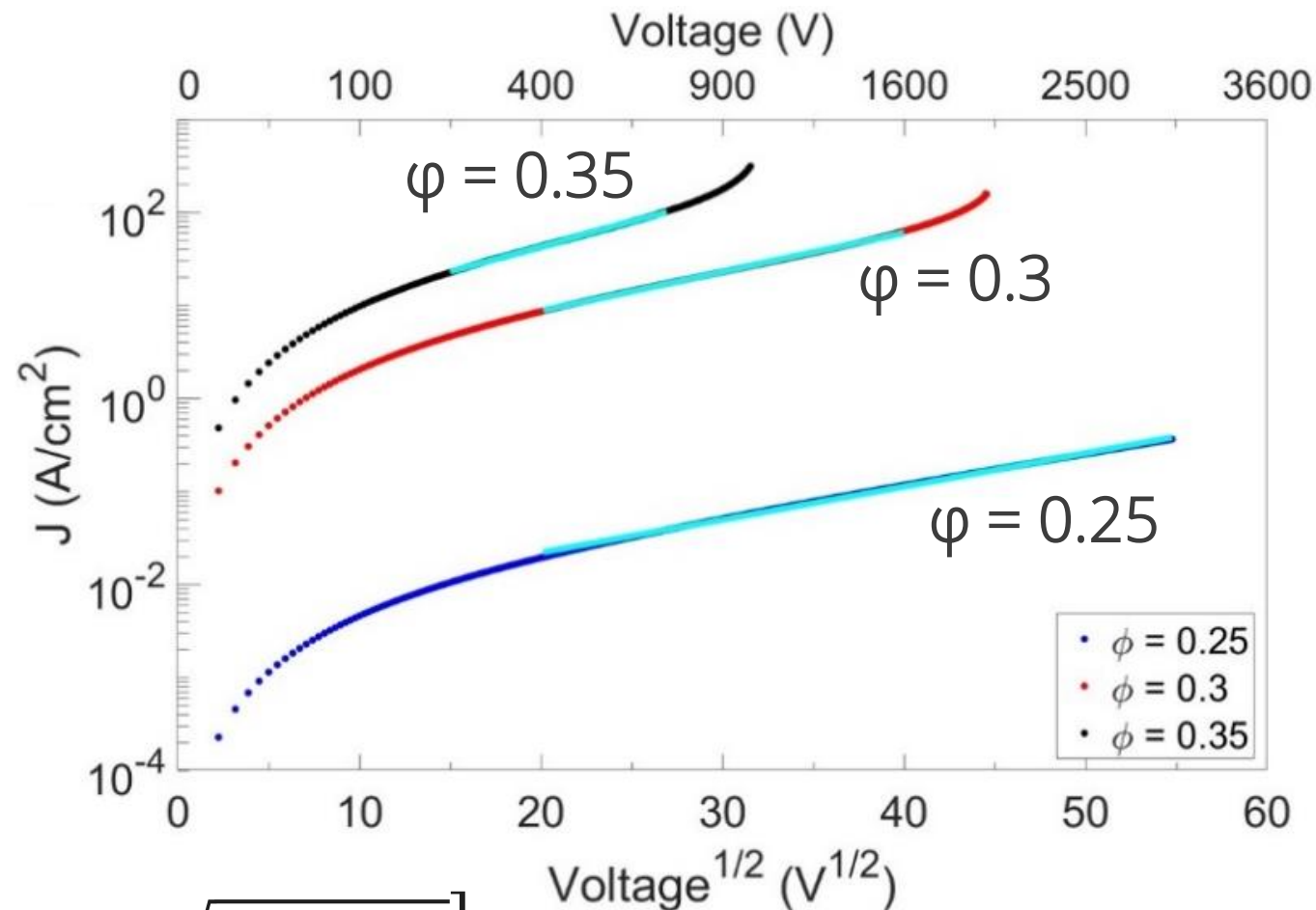
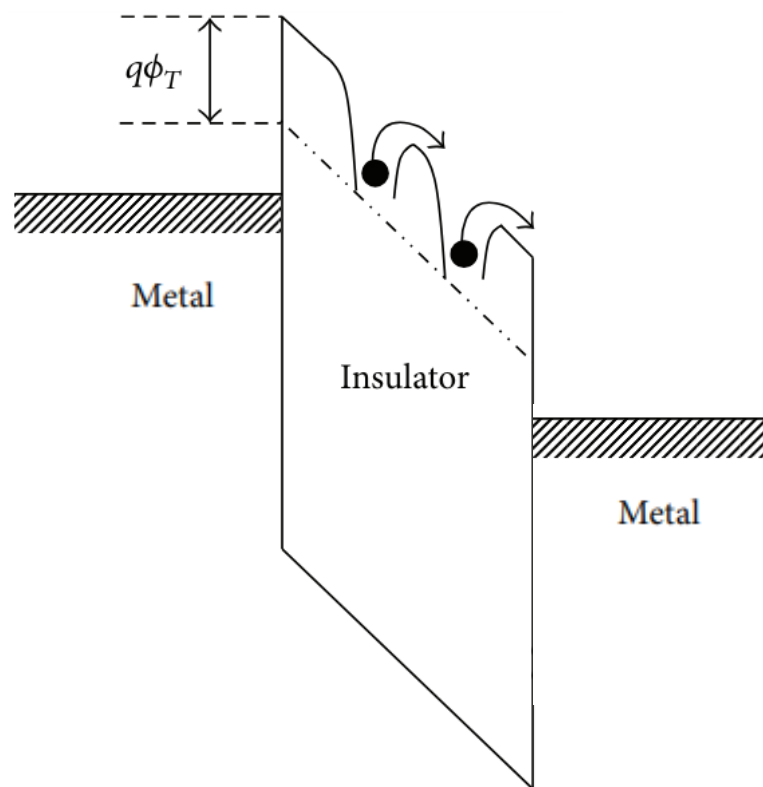
Ohmic conduction up to ~20 kV/cm



Poole-Frenkel emission for electric fields >20 kV/cm

Mo-SiN_x grown in 10% N₂

Poole-Frenkel Emission



$$\sigma \propto \exp \left[(q/k_B T) \sqrt{qE/\epsilon_0 \epsilon_r} \right]$$

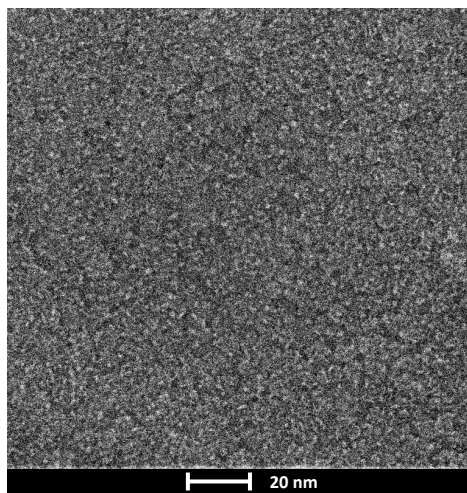
Maximum voltage limited by equipment NOT material.



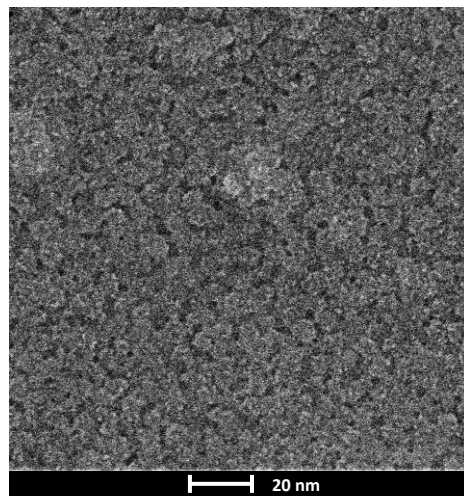
Annealing Increases Nanoparticle Size and Separation

Co-SiN_x grown in 50% N₂ ($\phi=0.35$)

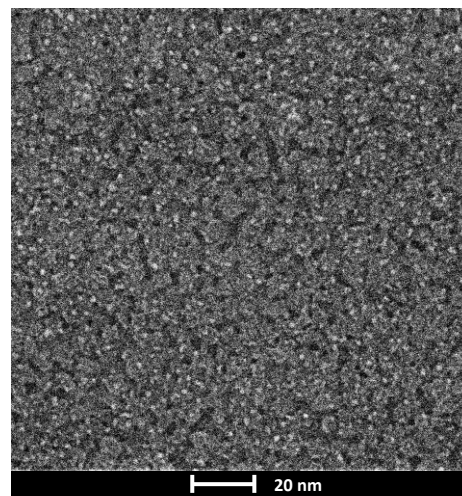
unannealed



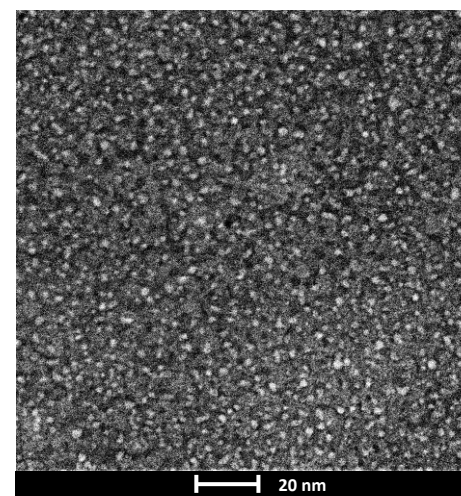
300 °C



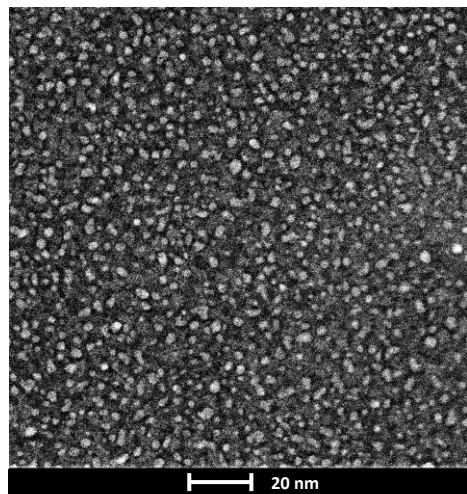
400 °C



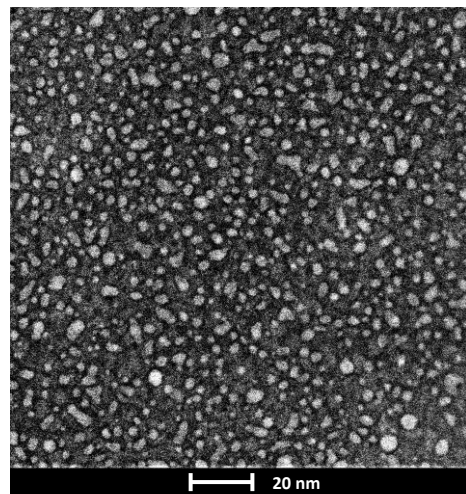
500 °C



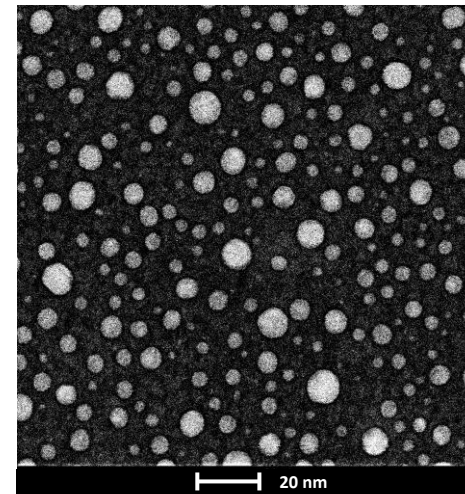
600 °C



700 °C



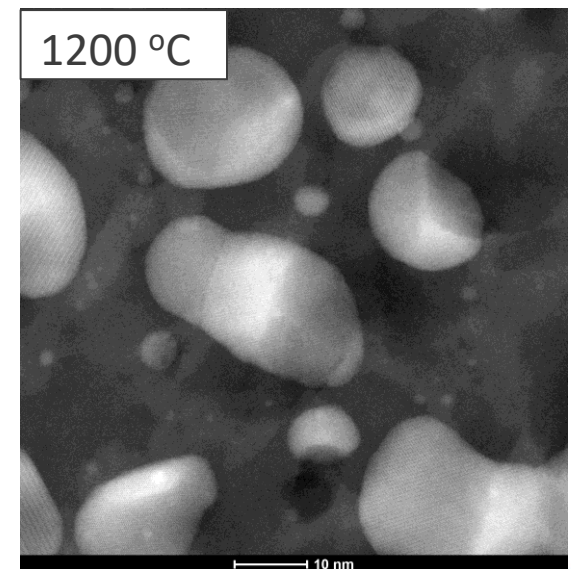
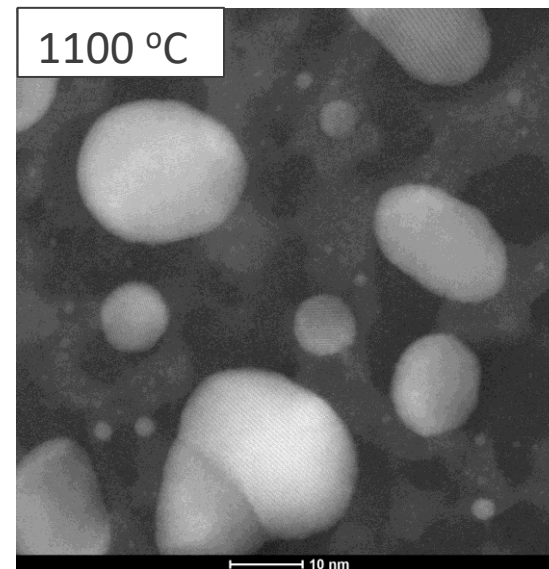
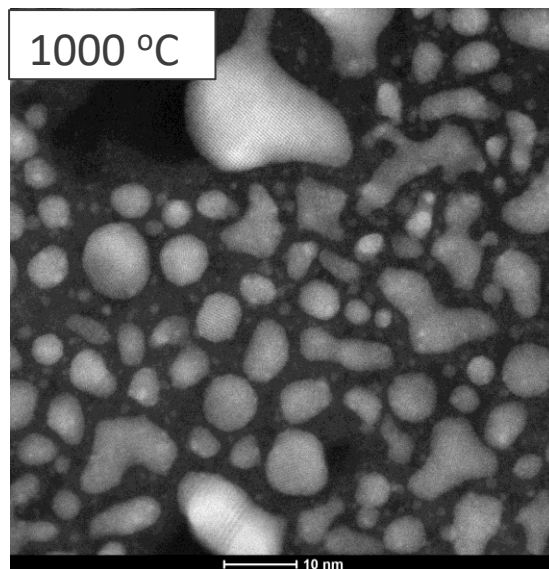
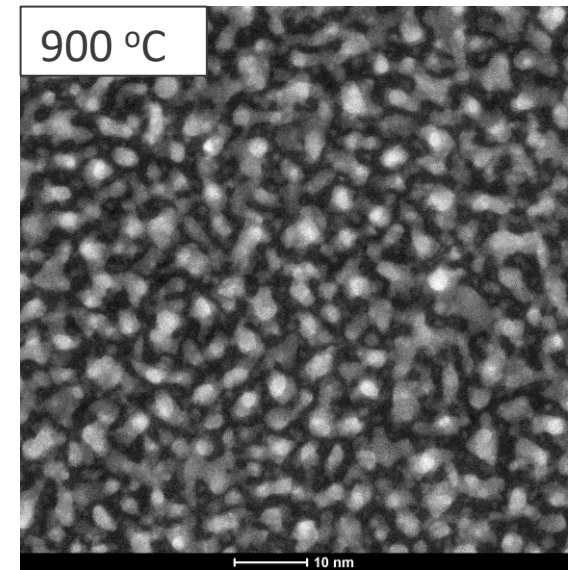
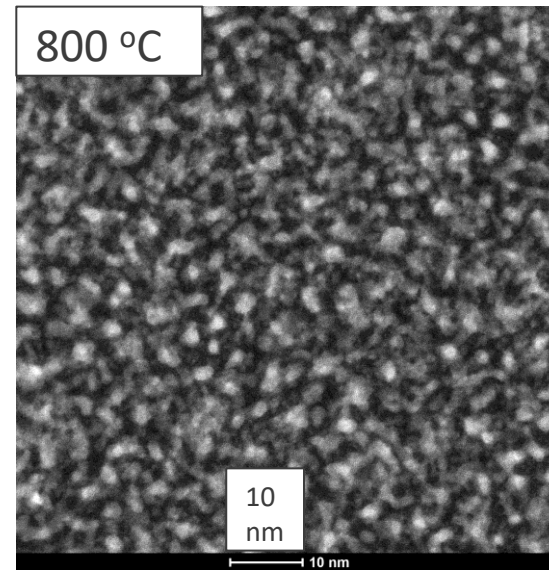
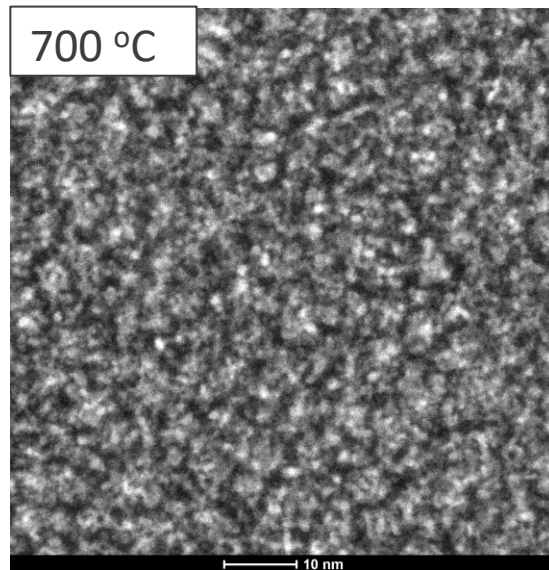
1000 °C





Mo-SiN_x is stable up to ~800 °C

Mo-SiN_x grown in 10% N₂ ($\phi=0.4$)

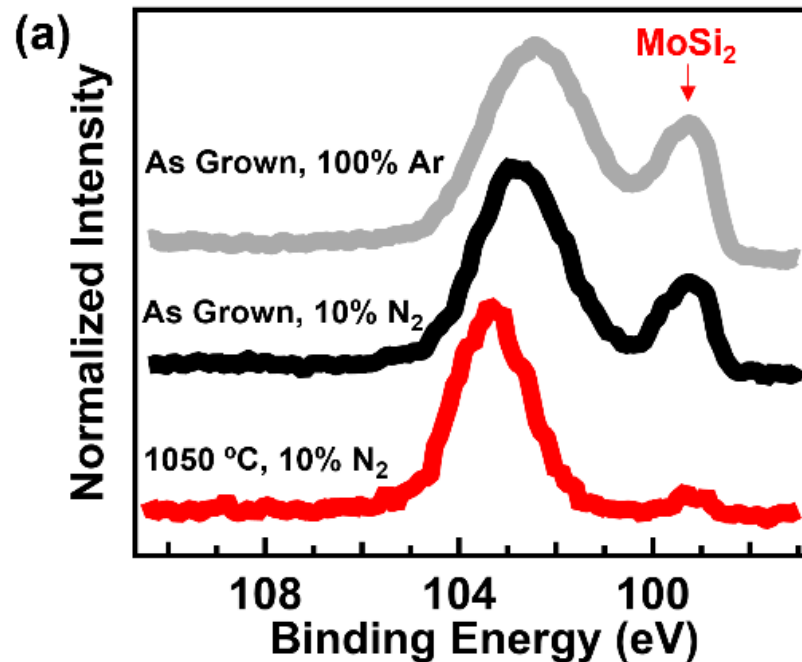


M. McGarry et al., in progress

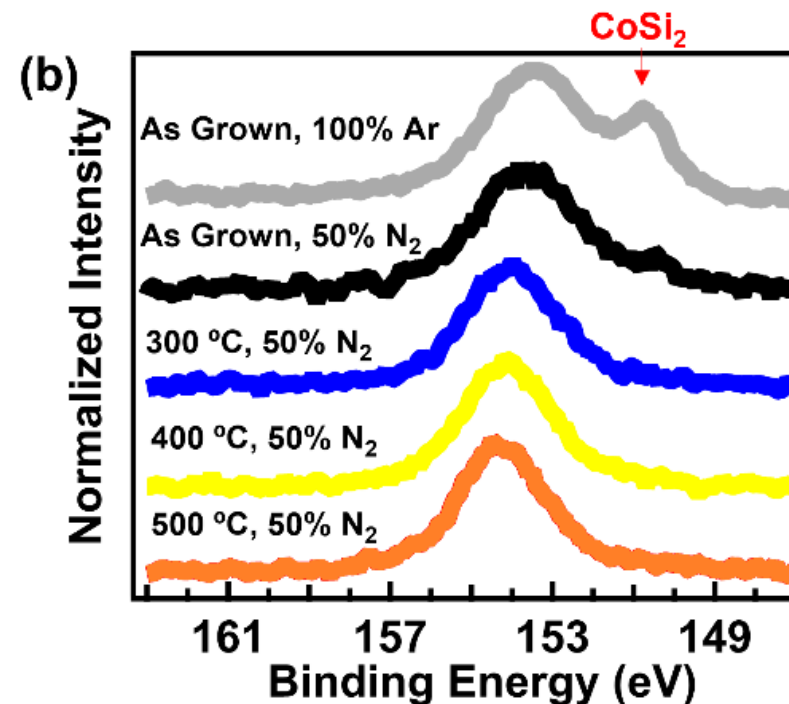


Deposition in N₂ and Annealing Reduce Metal-Silicide Content

Mo-SiN_x Si 2p spectra



Co-SiN_x Si 2s spectra



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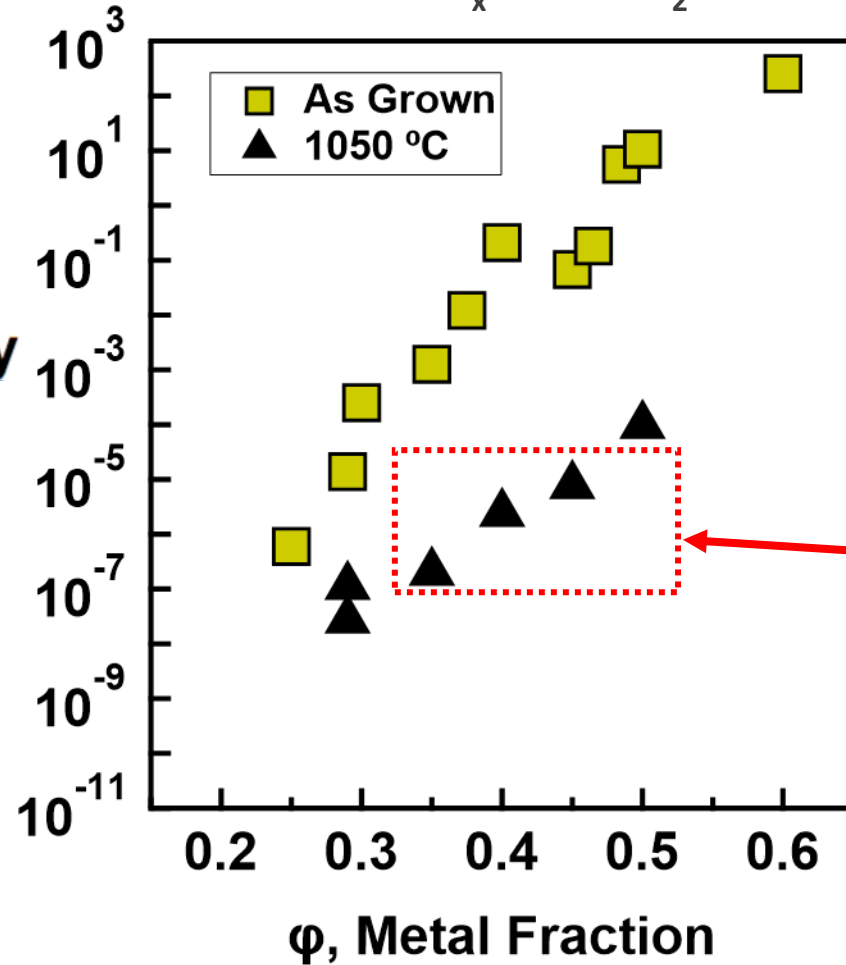
Group	Compound	$\Delta_f H$ (kJ*mol ⁻¹ *atom ⁻¹)	Ref.
Silicon nitride	Si ₃ N ₄	-118	1
Mo-silicides	Mo ₃ Si	-31	2
	Mo ₅ Si ₃	-39	3
	MoSi ₂	-46	4
Co-silicides	Co ₂ Si	-41	5
	CoSi	-48	5
	CoSi ₂	-33	5

1. P. A. G. O'Hare et al., The Journal of Chemical Thermodynamics **31** (3), 303-322 (1999).
2. I. Tomaszewicz et al., The Journal of Chemical Thermodynamics **28** (1), 29-42 (1996).
3. I. Tomaszewicz et al., The Journal of Chemical Thermodynamics **29** (1), 87-98 (1997).
4. P. A. G. O'Hare et al., The Journal of Chemical Thermodynamics **25** (11), 1333-1343 (1993).
5. D. Lexa et al., Chemistry of Materials **8** (11), 2636-2642 (1996).



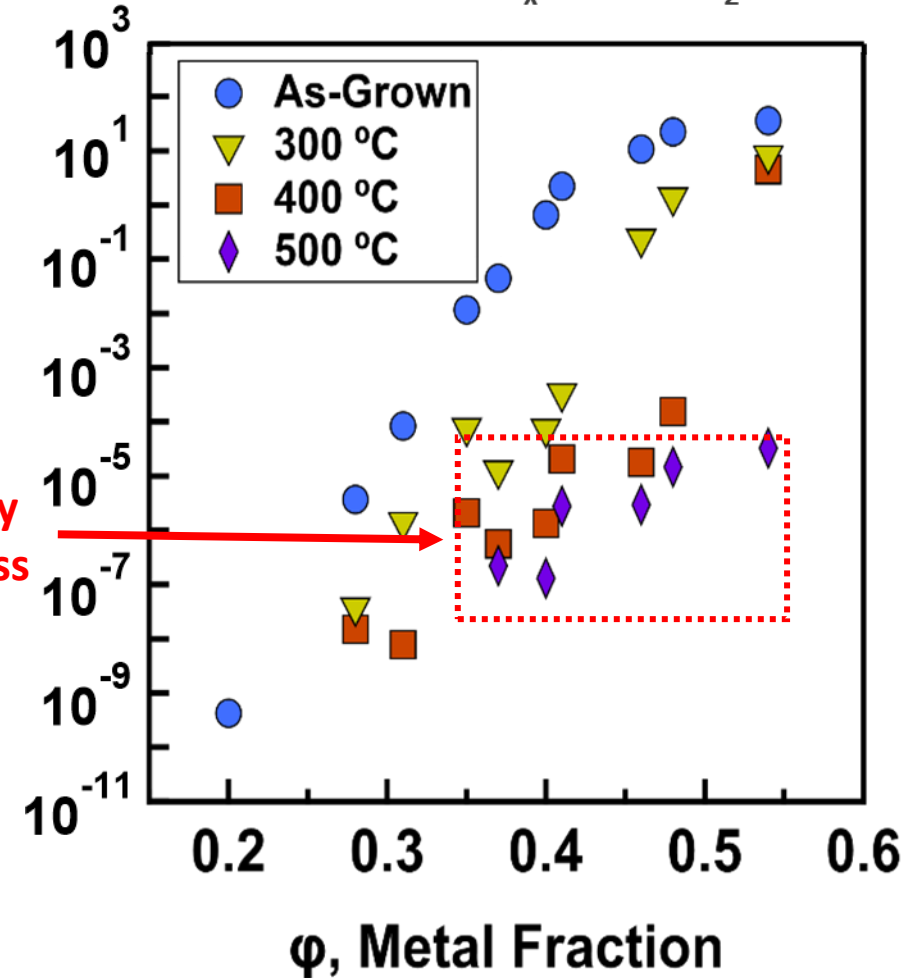
Annealing further improves insulator quality.

Mo-SiN_x in 10% N₂



M. McGarry et al., in progress

Co-SiN_x in 50% N₂



S.J. Gilbert et al., in progress

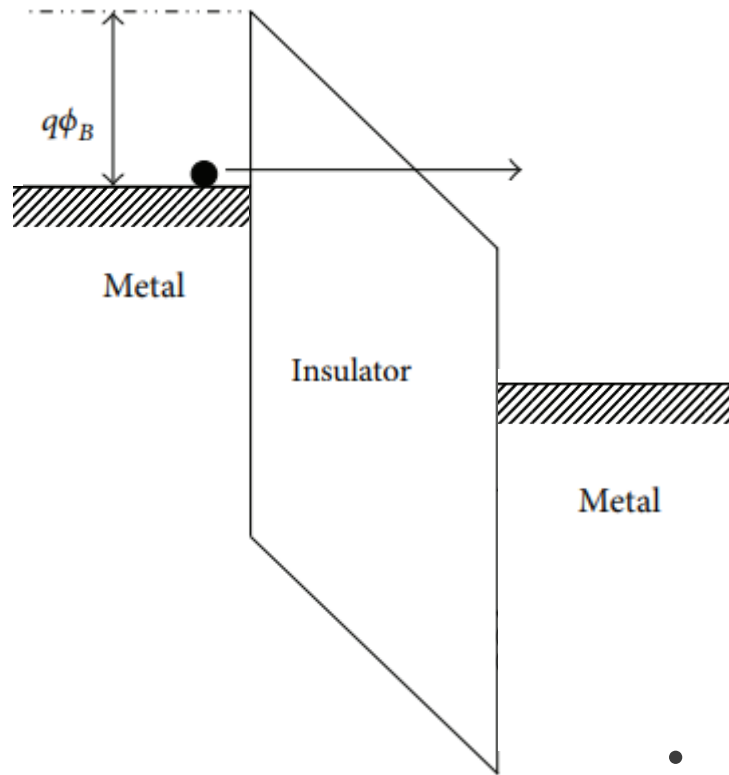
Potential protection devices with $\geq 50\%$ metal fraction.



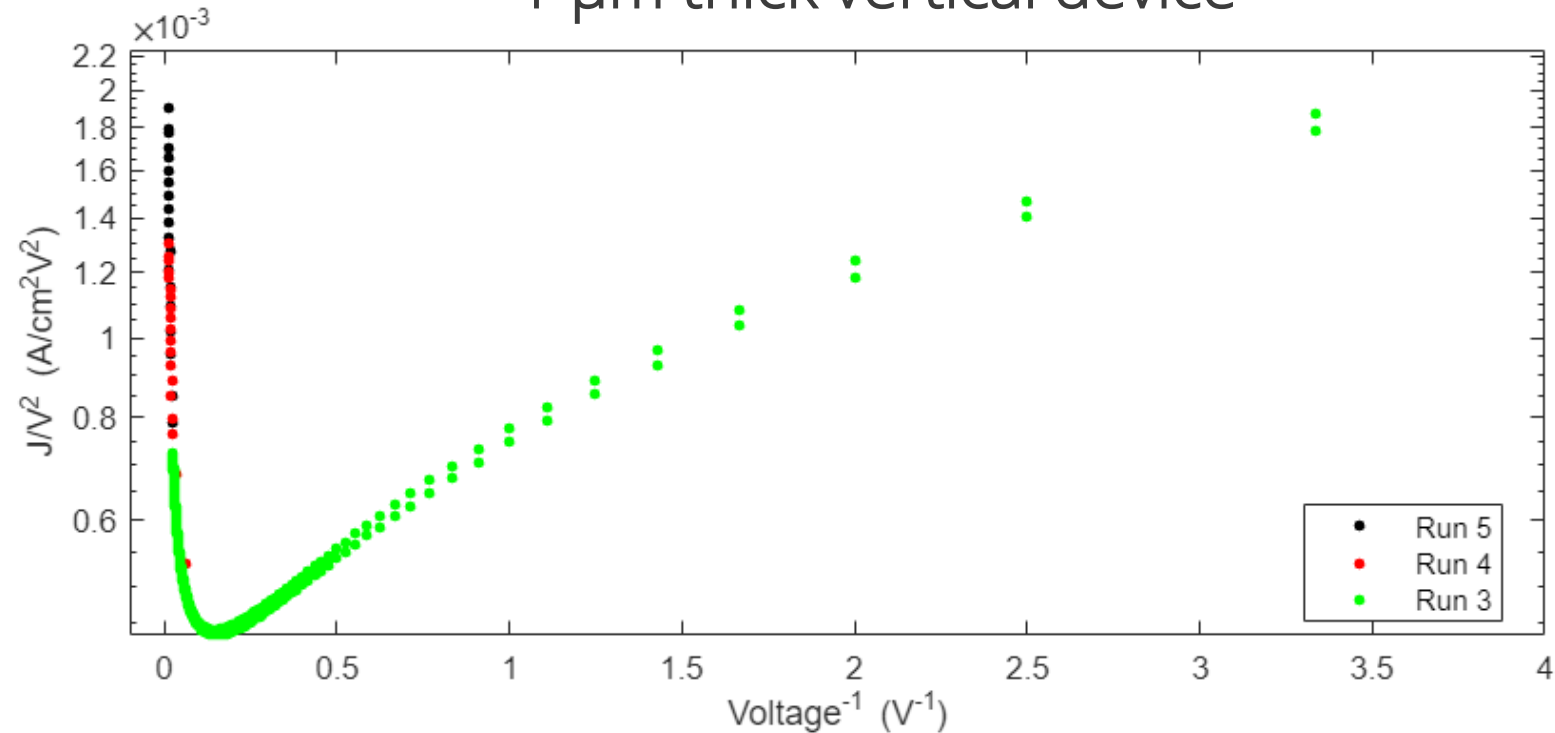
Fowler-Nordheim tunneling enhances current carrying capacity

Mo-SiN_x grown in 10% N₂
 $\phi = 0.3$, 1050 °C anneal
1 μm thick vertical device

Fowler-Nordheim Tunneling



$$\sigma \propto E^2 \exp(E_0/E)$$



M. McGarry et al., in progress

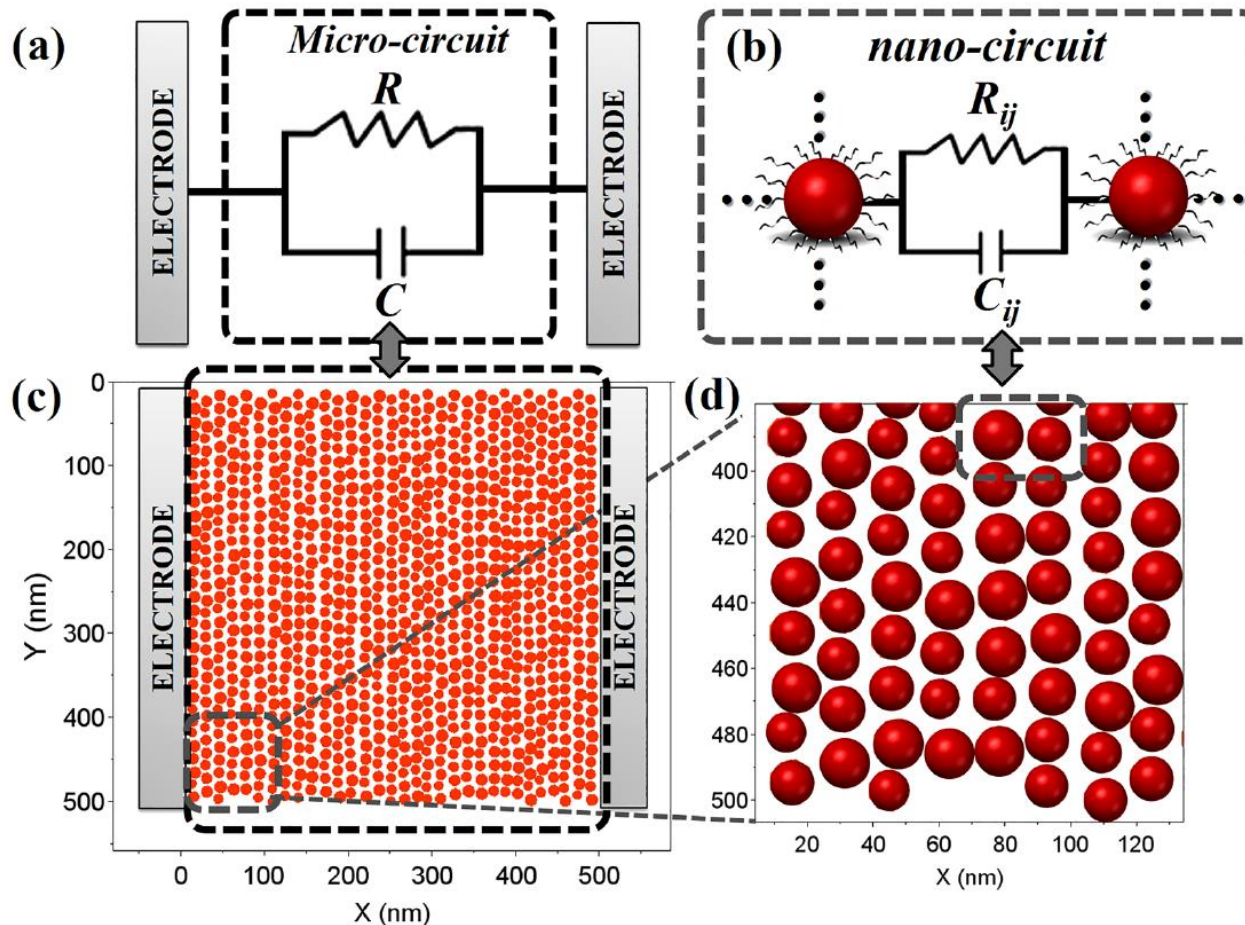
- High breakdown strength (>0.8 MV/cm) allows for compact devices.
- Current densities measured up to 10 A/cm².



High frequencies also enhance GM conductivity.

Complementary tunneling and capacitive conduction paths.

GMs follow Jonscher's universal power law



$$\sigma_{AC}'(\omega) = \sigma_{DC} + A\omega^n$$

Tunneling dominates at low frequencies.

Capacitive transport dominates at high frequencies.

L. Merle et al., J. Appl. Phys. **132** (1), 015107 (2022).

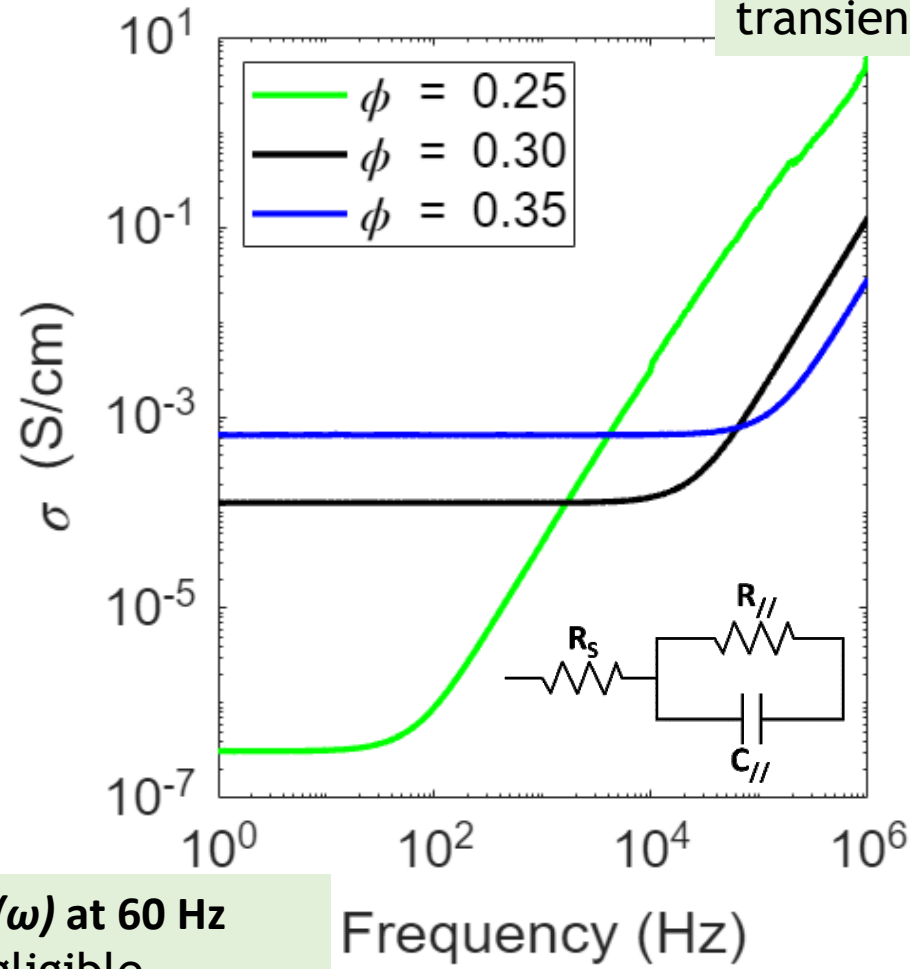


33

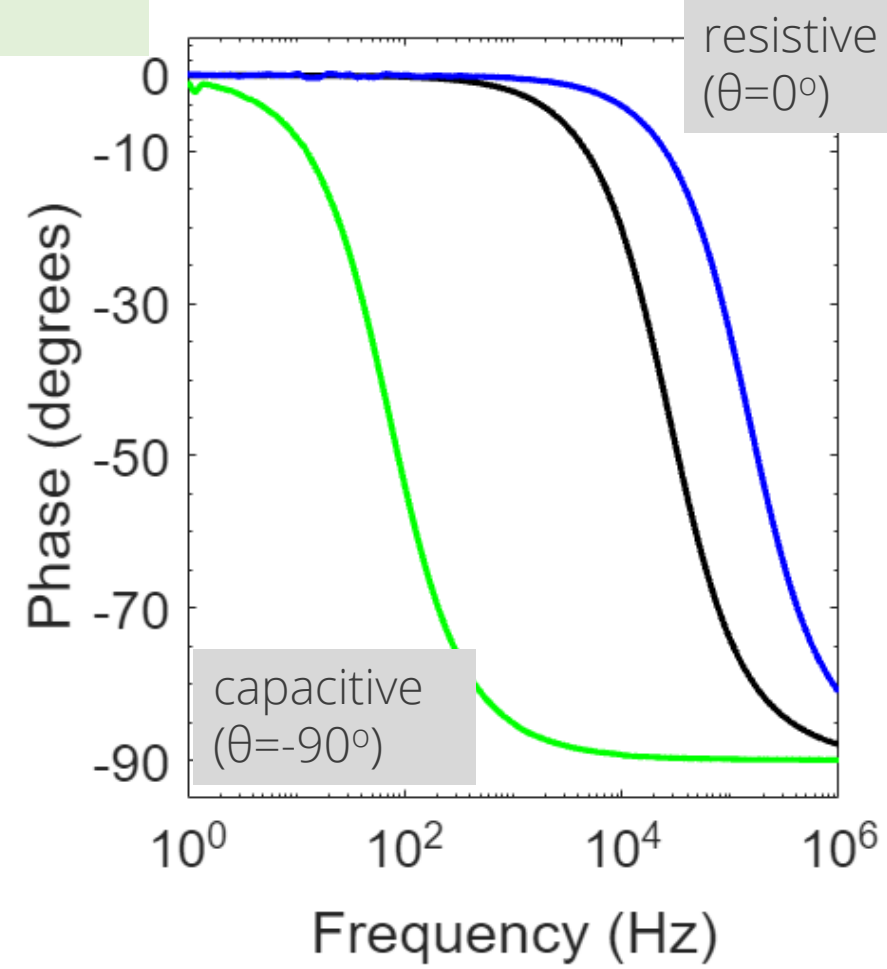
Material advances result in extraordinarily σ_{AC} response

Mo-SiN_x grown in 10% N₂

High $\sigma(\omega)$ at MHz
→ Shunt ns
transients



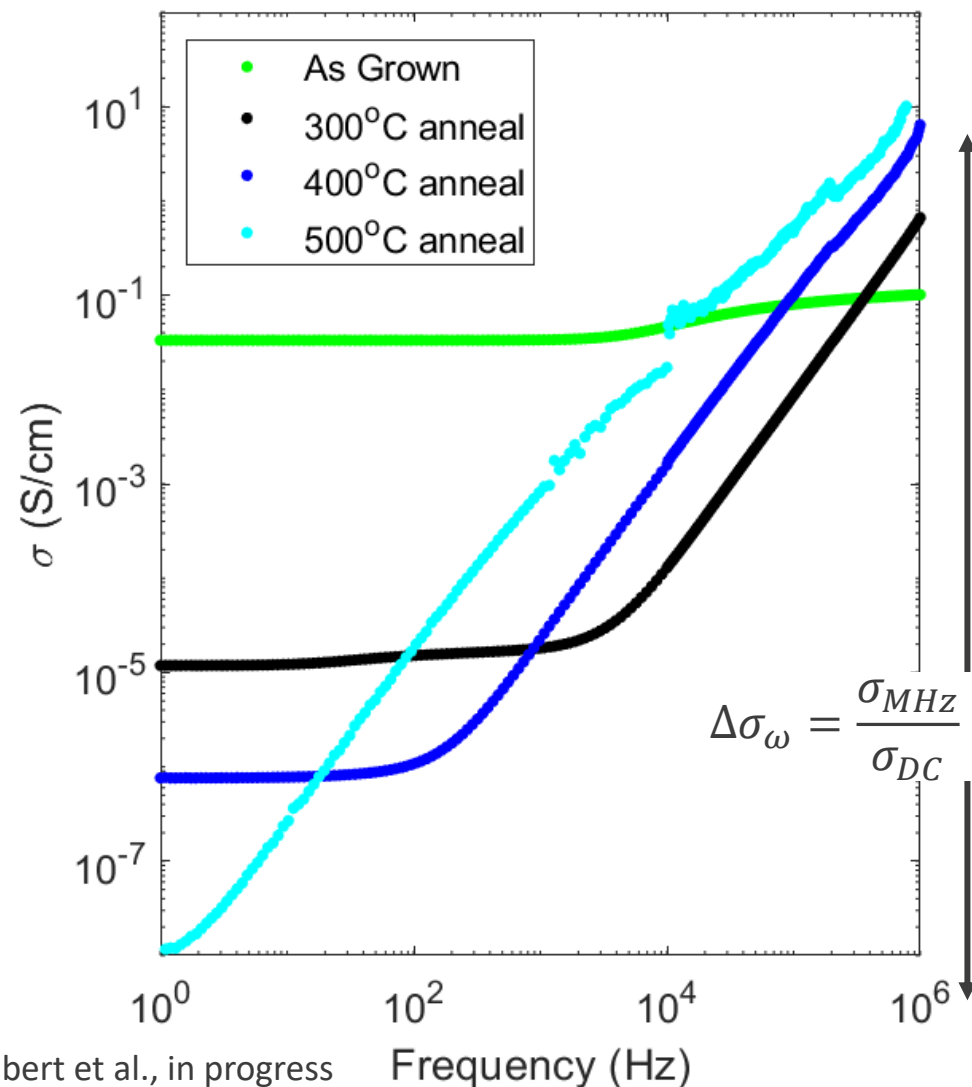
Low $\sigma(\omega)$ at 60 Hz
→ Negligible
leakage current



M. McGarry et al., submitted

Material advances result in extraordinarily σ_{AC} response

Co-SiN_x, grown in 50% N₂, $\varphi = 0.4$



S.J. Gilbert et al., in progress

GM	Annealing	φ	$\Delta\sigma_{\omega}$
<i>Literature</i>			
Pd-ZrO ₂ [1]	As Grown	0.28	50
(FeCoZr) _x (PZT) _(100-x) [2]	As Grown	0.52	100
Pt-SiO ₂ [3]	As Grown	0.3-0.6	$10^3 - 10^4$
<i>This LDRD</i>			
Mo-SiN _x , 10% N ₂	As Grown	0.35	40
Mo-SiN _x , 10% N ₂	As Grown	0.30	10^3
Mo-SiN _x , 10% N ₂	As Grown	0.25	10^7
Mo-SiN _x , 10% N ₂	1050 °C	0.29	10^8
Co-SiN _x , 50% N ₂	As Grown	0.4	<10
Co-SiN _x , 50% N ₂	300 °C	0.4	10^5
Co-SiN _x , 50% N ₂	400 °C	0.4	10^7
Co-SiN _x , 50% N ₂	500 °C	0.4	10^9

1. H. Bakkali et al., Sci. Rep. **6**, 29676 (2016).
2. O. Boiko et al., AIP Advances **12** (2), 025306 (2022).
3. N. Moyo and K. Leaver, J. Phys. D: Appl. Phys. **13** (8), 1511 (1980).



Conclusion: Granular Metals are promising for nanosecond high voltage transient protection

- ✓ compact
 - ✓ insulating at 60 Hz and low electric fields
 - ✓ high thermal stability
 - ✓ conducting for 1 GHz voltage spikes
 - ? □ large current carrying capacity ($>1 \text{ kA/cm}^2$)
- $>1 \text{ MV/cm}$ breakdown strength
 - Conductivities of 10^{-5} - 10^{-7} S/cm
 - Mo-SiN_x stable to $\sim 800^\circ \text{C}$
 - $>10^6$ conductivity increase at 1 MHz
 - Coupled high frequency/electric-field measurements needed.

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